

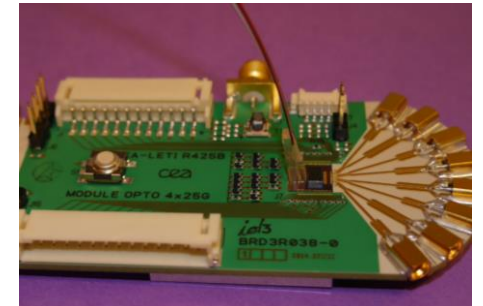
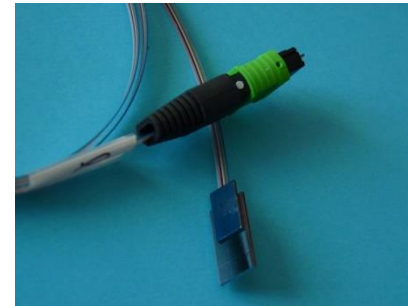
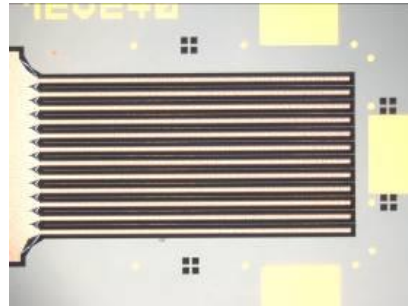
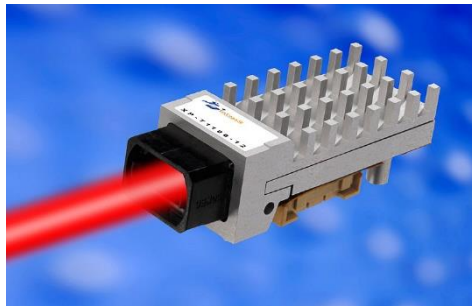
ADVANCED PACKAGING FOR SILICON PHOTONICS BASED MODULES AND APPLICATIONS

EPS Webinar | Stéphane Bernabé | 25.06.19

- **Silicon Photonics**
 - Promises
 - Challenges
 - What can advanced packaging bring to PIC modules ?
 - Some work in progress



Bio: Stéphane Bernabé is the head of the Photonic Packaging Lab at CEA-LETI, Grenoble, France. His field of expertise is in Photonic Integrated Circuit packaging, Module integration (VCSEL and PIC), and Electronic/Photonic convergence for advanced applications of PICs. He previously led several R&D projects dealing with these topics and is currently involved in the EU-funded projects MASSTART, PIXAPP, and TINKER. He has also overseen module and packaging developments in companies Radiall and Intexys Photonics. He's a member of the Electronics Packaging Society (IEEE-EPS) and acts as committee member in the ESTC and ECTC conferences. He has co-authored 50 papers, 3 book chapters and holds 15 patents in the field of photonics packaging.



“3rd Innovative Public Research Organization Worldwide” 2012 -2020



Since **1967**



2,000 people



Patents:

- > 3,000 in portfolio
- 40% under license agreement



Startups:

- 68 created for 20 years (75% in activity)
- 3500 jobs created



Cleanrooms:

- 500 state-of-the-art equipment in 200 & 300 m²
- 10 000 square meters cleanroom



Budget:

- 315 M€
- 85% from R&D contracts

Founded in 1967, based in France (Grenoble) with offices in USA and Japan



- 12600 m² incl. offices, labs and clean rooms
- Dedicated clean rooms for III-V and II-VI materials (growth, epitaxy, process and packaging) on versatile substrate geometries up to 150 mm
- Electro-optical test and characterization facilities
- Design and simulation capabilities for process, growth, optics



400 people



Patents:

- 80 per year
- > 700 in portfolio
- 40 % under license agreement



Budget:

- 70 M€
- 90% from R&D contracts

CEA-LETI 8,500 m² CLEAN ROOMS for 200mm & 300mm wafers



LETI PHOTONICS DIVISION

Our mission : innovate by miniaturizing and integrating optical components for our industrial partners



Display

High brightness and 3D display components and systems



High-end Infrared Imaging

High performance IR image sensors for military, space and industrial applications



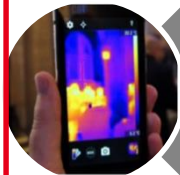
X and γ imaging systems

Security, non destructive test, healthcare



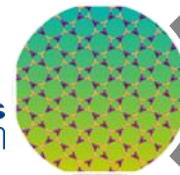
Integrated optics on Si

Integrated transceiver, receivers and sensors on silicon, VCSELs



Thermal and THz imaging

Toward low cost microbolometer matrices for consumer applications



Materials

Crystal growth, epitaxy, substrate preparation



Optical sensors

MIR integrated gas sensors and analyzers. Particle detection



CMOS image sensors

Advanced image sensors and systems for 3D imaging



Semiconductor process

Miniaturization and integration technologies from 100 to 300 mm



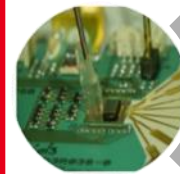
Solid-state lighting

LED matrices for industrial and automotive applications



3D imaging systems

Compact, smart, low cost lidars 3D image modules

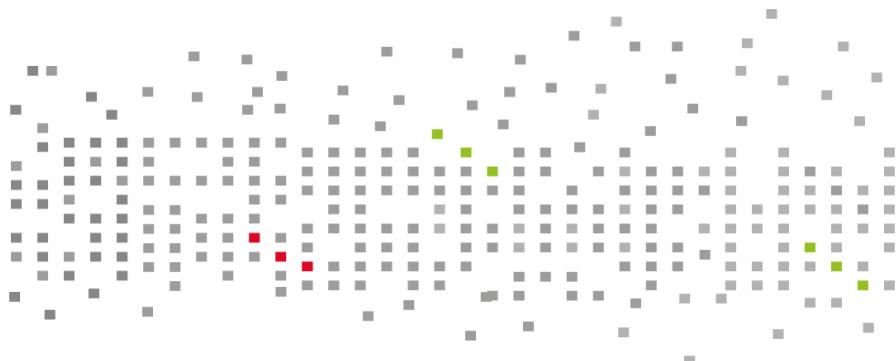
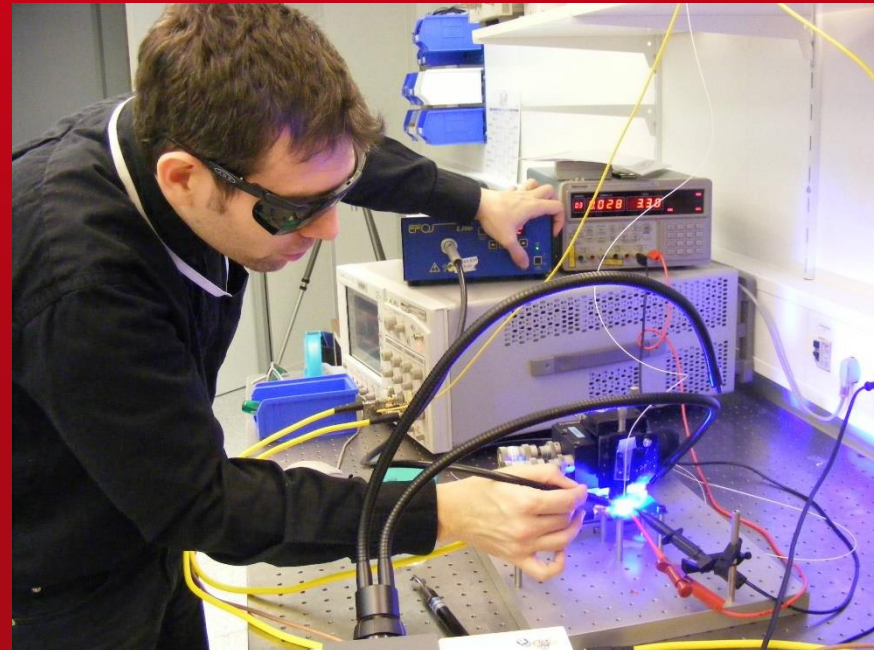


Packaging and assembly

Optics-electronics assembly, optical interfaces, component curvature

A SHORT HISTORY OF INTEGRATED OPTICS PACKAGING

BASED ON MY OWN EXPERIENCE ON ALIGNING,
GLUING AND TESTING FIBERS TO PICS



EARLY STUDIES ON INTEGRATED OPTICS PACKAGING (70'S)

End fire coupling between optical fibers and diffused channel waveguides

W. K. Burns and G. B. Hocker

W. K. Burns is with U.S. Naval Research Laboratory, Washington, D. C. 20375; G. B. Hocker is with Honeywell Corporate Research Center, Bloomington, Minnesota 55420.

Received 24 February 1977.

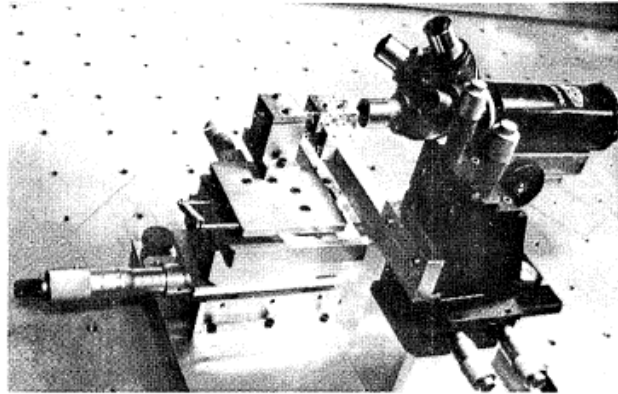


Fig. 1. Connecting equipment.

A waveguide to single-mode fiber coupler has been devised, and its coupling characteristics have been investigated experimentally. This method can provide highly accurate optical alignment between a fiber and a waveguide and is applicable for connecting a laser source or a detector to a fiber. The coupler has a special feature wherein degradation in coupling, yielded by fiber displacement after the connection, can be reset to the initial state. Present coupling loss is large because of insufficient optical field overlap between the fiber and the waveguide. Therefore, further technical improvement to fabricate the waveguide with the optical field close to that of the fiber is necessary for coupling loss reduction. Especially, Li_2O out-diffusion is one of the difficult problems which must be overcome in fabricating a narrow strip waveguide. More detailed investigation on coupling efficiency degradation due to aging effect or temperature variation will be made.

Single-mode optical-waveguide fiber coupler

Juichi Noda, Osamu Mikami, Makoto Minakata, and Masaharu Fukuma

A single-mode fiber coupler to the Ti diffused LiNbO_3 strip waveguide has been devised. The influences of three axial displacements and two angular misalignments on the coupling efficiency have been investigated at 6328-Å wavelength. The coupler has a special feature wherein coupling degradation caused by fiber displacement after connection can be recovered to the initial state. The total optical insertion loss is 3 dB after fixing the fiber to the LiNbO_3 strip waveguide, which is 4 μm wide and 8 mm long.

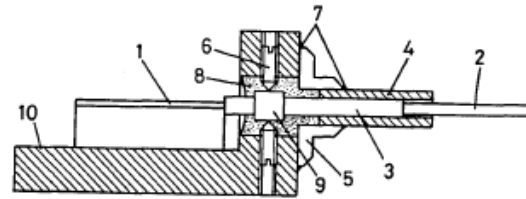


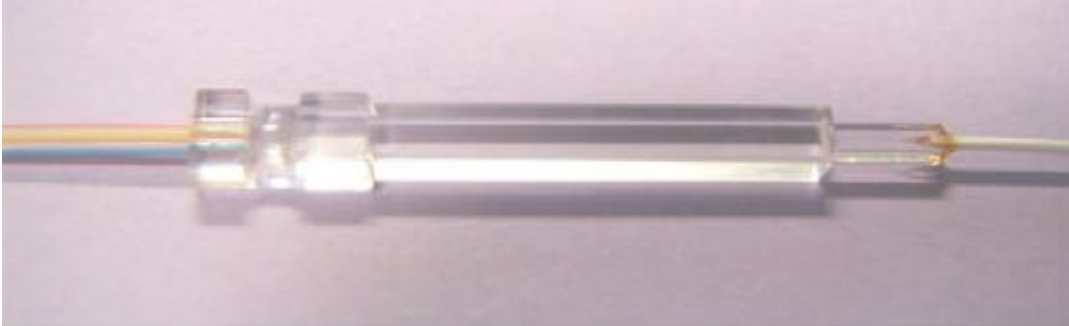
Fig. 2. Structure of the connection jig. This view shows the state after fixing the fiber to the waveguide—1: strip waveguide; 2: fiber; 3: stainless steel pipe; 4: sleeve; 5: flange; 6: set screws; 7: adhesive paste; 8: mold; 9: square block; 10: case.

2K YEARS : PIGTAILING IS BECOMING MATURE

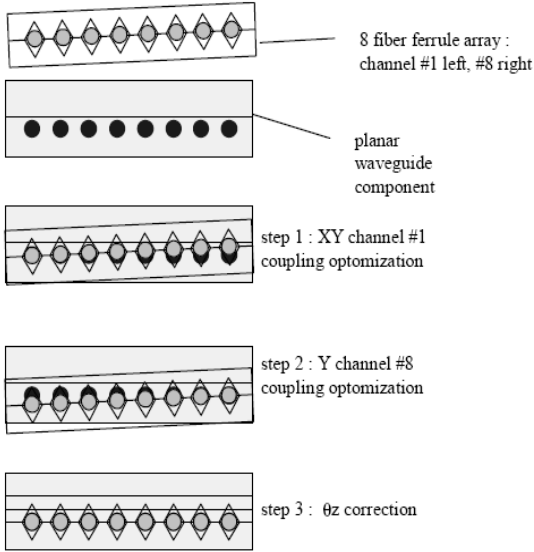
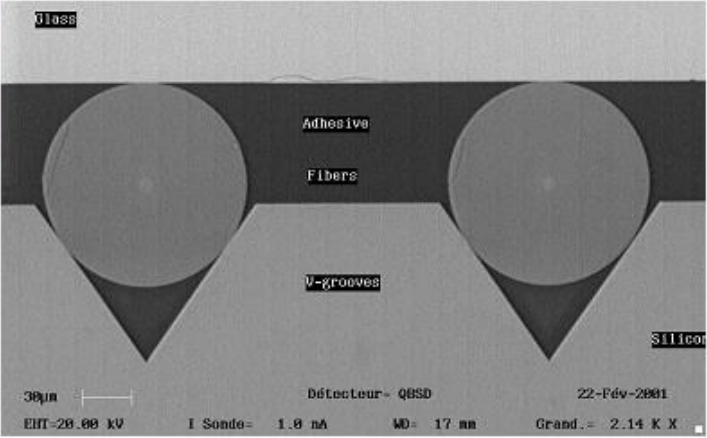
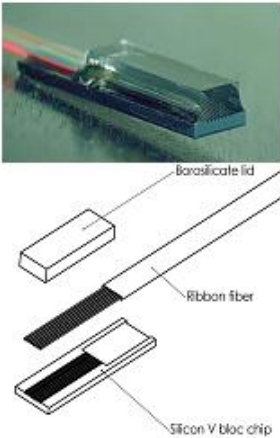
Boom of optical devices

Several PIC technologies :

- Glass
- Silica On Silicon
- Lithium Niobate (for modulators)
- ASOC from Bookham (thick SOI)



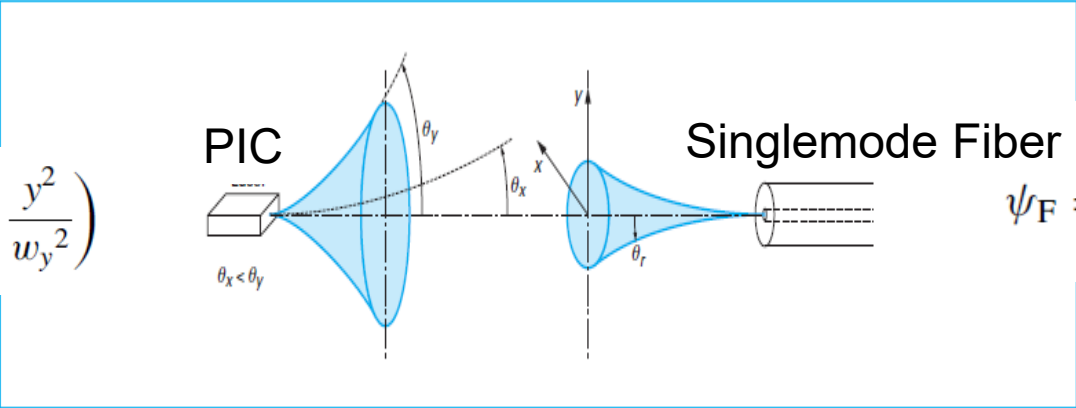
Glass optical 1x8 splitter, from Teem Photonics



WHAT A PACKAGING ENGINEER SHOULD KNOW ABOUT (SINGLEMODE) PHOTONICS

PIC mode

$$\psi_b = \sqrt{\frac{2}{\pi w_x w_y}} \exp\left(-\frac{x^2}{w_x^2}\right) \exp\left(-\frac{y^2}{w_y^2}\right)$$



Fiber

$$\psi_F = \sqrt{\frac{2}{\pi}} \frac{1}{w_F} \exp\left(-\frac{r^2}{w_F^2}\right)$$

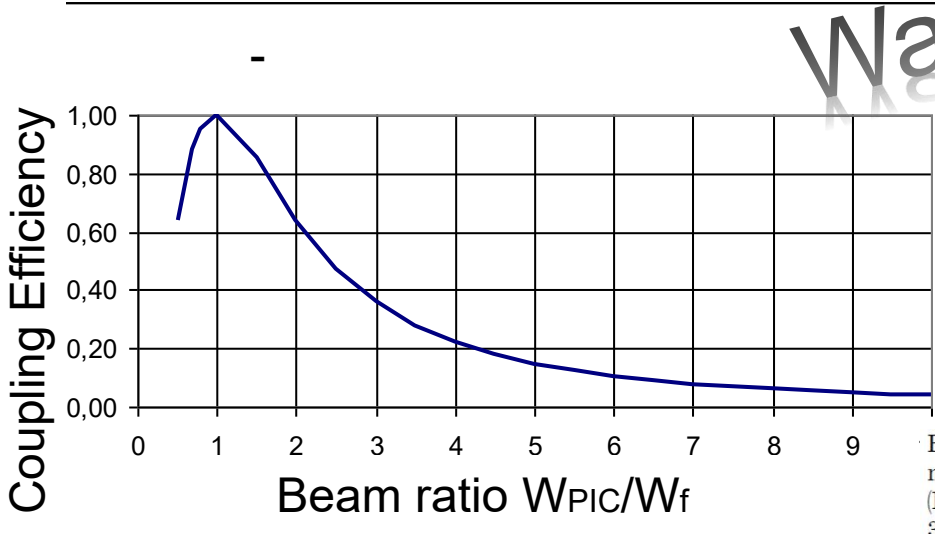
Figure 11 - Schéma de couplage entre une diode laser et une fibre optique

Coupling Efficiency

$$\eta = \frac{4}{\left(\frac{\omega_{0x}}{\omega_f} + \frac{\omega_f}{\omega_{0x}}\right) \cdot \left(\frac{\omega_{0y}}{\omega_f} + \frac{\omega_f}{\omega_{0y}}\right)}$$

$$\eta_{opt} = \frac{4\varepsilon}{(\varepsilon + 1)^2}$$

Ellipticity of PIC beam



Waist is the key!

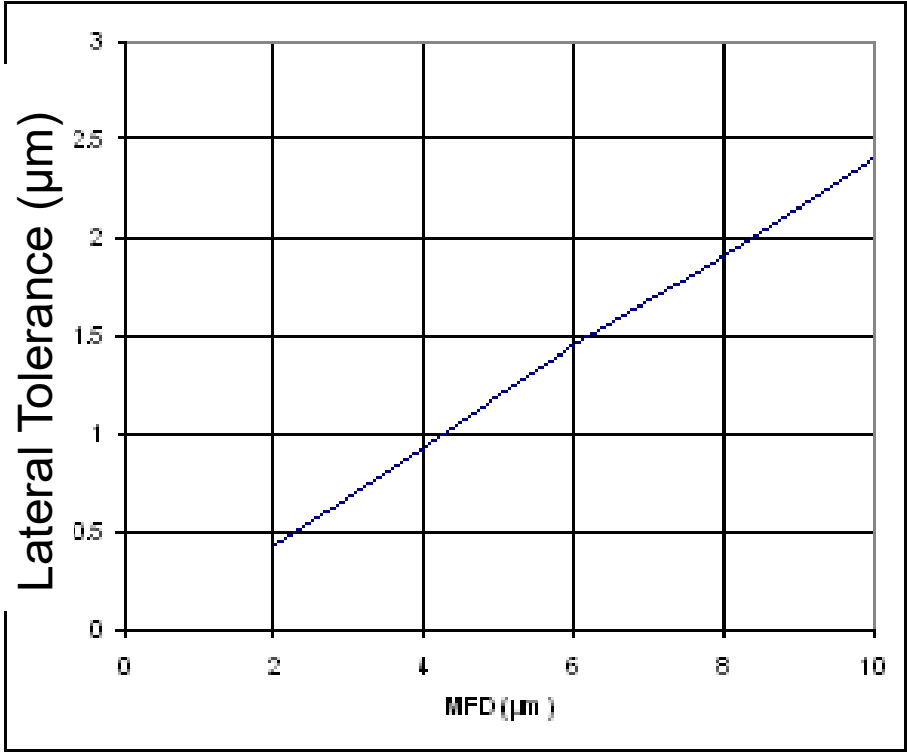
Available in the following configuration :

- Butt coupling (z=0, no gap)
- No tilt
- No offset along x nor y

H. Kogelnik, "Coupling and conversion coefficients for optical modes," in *Microwave Research Institute Symposia Series 14* (Polytechnic Institute of Brooklyn, New York, 1964), pp. 333-347.
 W. B. Joyce, "Alignment of Gaussian beams," *Appl. Opt.* **23**, 4187-4196 (1984).

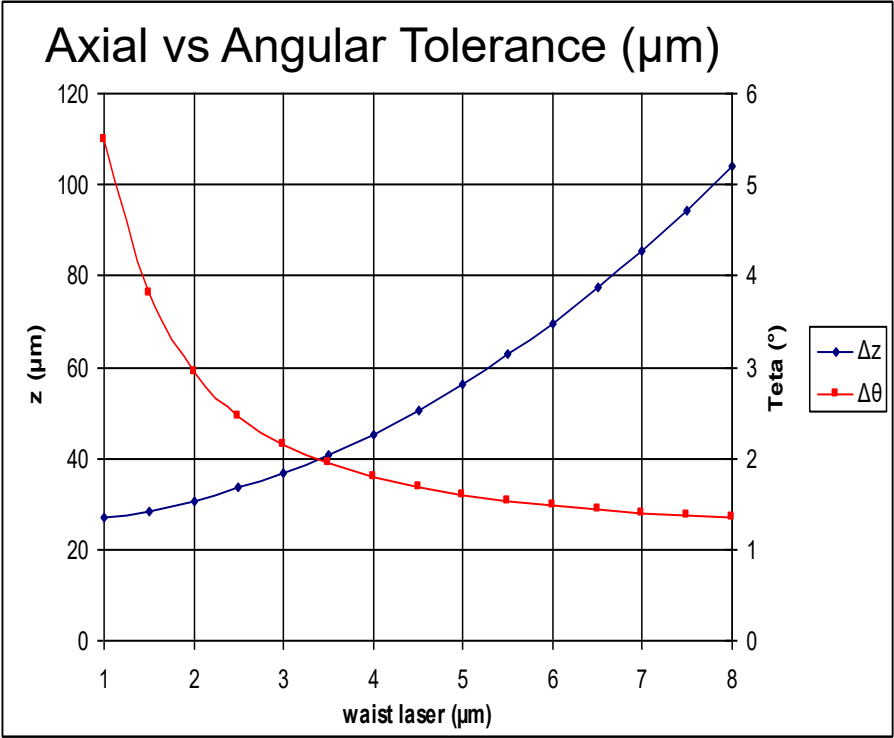
WHAT A PACKAGING ENGINEER SHOULD KNOW ABOUT (SINGLEMODE) PHOTONICS (2)

PIC packager Golden rule

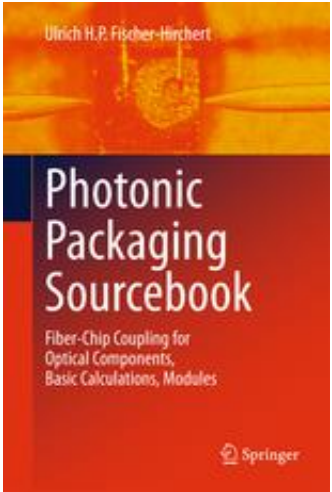
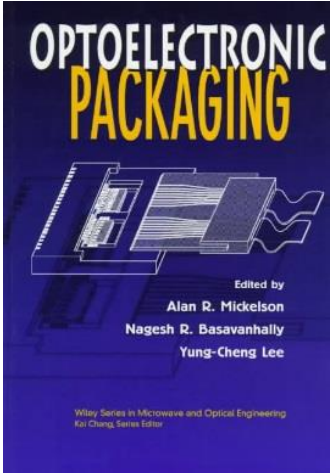


$$\Delta x = 0.33 \sqrt{(\omega^2 + \omega_f^2)}$$

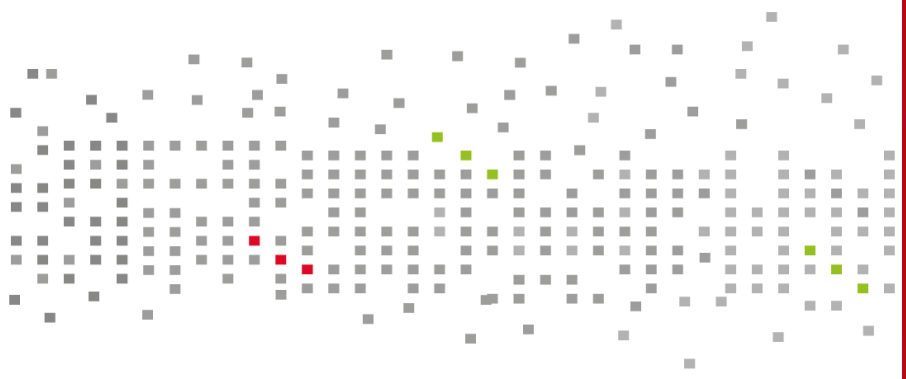
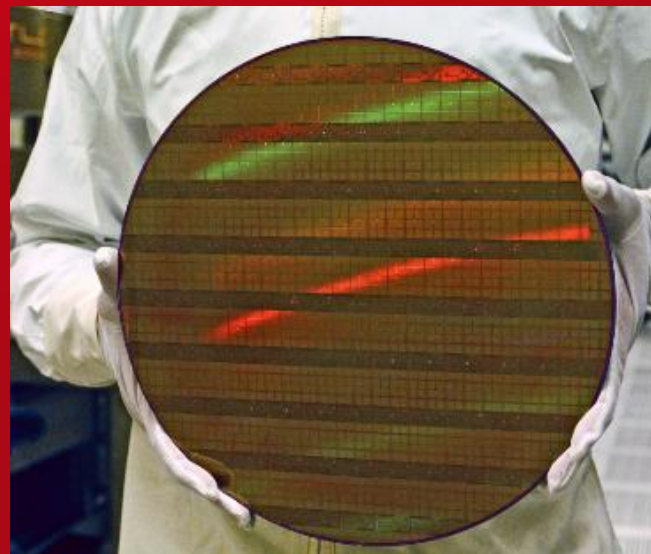
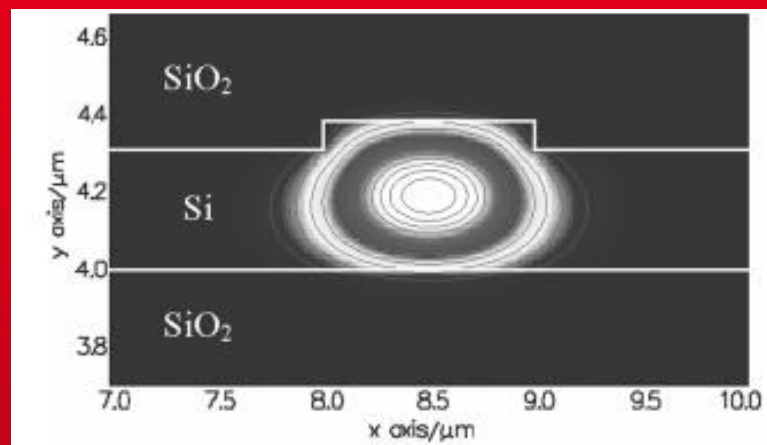
The offset/tilt trade-off



$$\Delta \theta = 60 \frac{\lambda}{\pi^2} \sqrt{\frac{1}{\omega^2} + \frac{1}{\omega_f^2}}$$

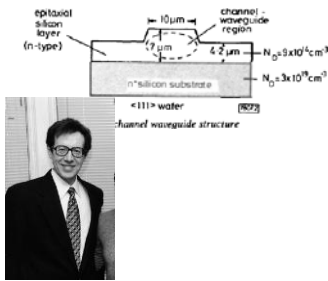


SILICON PHOTONICS : PLATFORM & ROADMAP



HISTORY

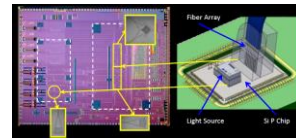
1985 Soref's paper on Si optical properties for modulation



1988-2003 Bookham ASOC devices



2001 Luxtera creation



Intel launches silicon photonics

The product, 16 years in the making, provides a solution as the cost of fiber optics in the datacenter grows.

By Stephanie Condon for Between the Lines | August 12, 2008 | 17:25 GMT (08:58 BST) | Topic: Data Centers

2016 : Intel, Acacia, MCom... launch SiPho products



2019 Cisco completes acquisition of Luxtera

2019 400G SiPho transceiver (Intel, Inphi, ...)



THE BELL SYSTEM
TECHNICAL JOURNAL

DEVOTED TO THE SCIENTIFIC AND ENGINEERING ASPECTS OF ELECTRICAL COMMUNICATION

Volume 48 September 1969 Number 7

Integrated Optics: An Introduction

By STEWART E. MILLER

This paper outlines a proposal for a miniature form of laser beam circuitry. Index of refraction changes of the order of 10^{-2} or 10^{-3} in a substrate such as glass allow guided laser beams of width near 10 microns. Photolithographic techniques may permit simultaneous construction of complex circuit patterns. This paper also indicates possible miniature forms for a laser, modulator, and hybrids. If realized, this new art would facilitate isolating the laser circuit assembly from thermal, mechanical, and acoustic ambient changes through small overall size; economy should ultimately result.

2002 J.M. Fedeli Pioneered SiPho at Leti



2008-2012 HELIOS project



2012-... III-V Lab IRT Nanoelec



III-V lab



DFB@1310nm + 32G EAM + SOA

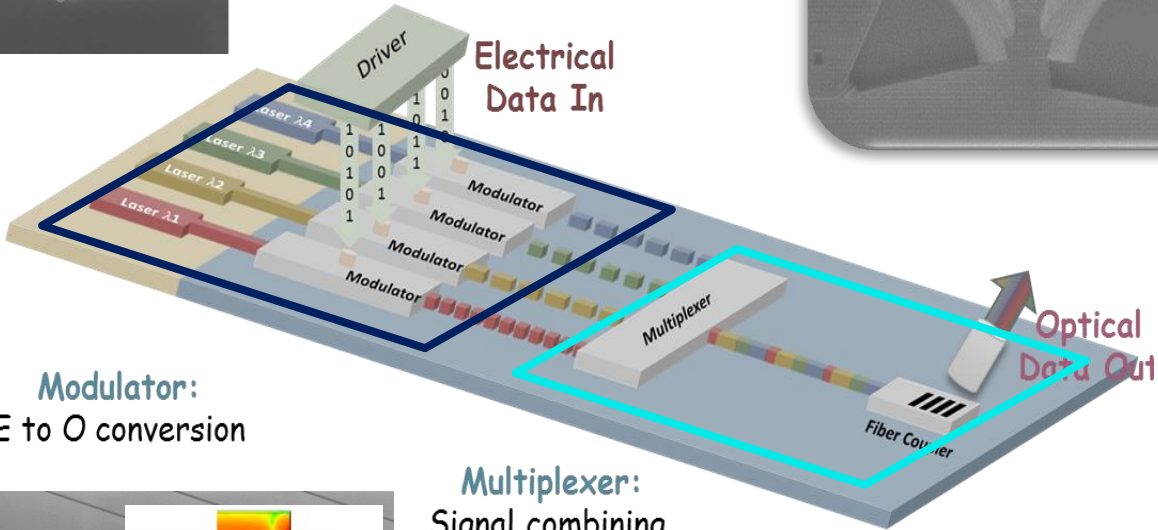
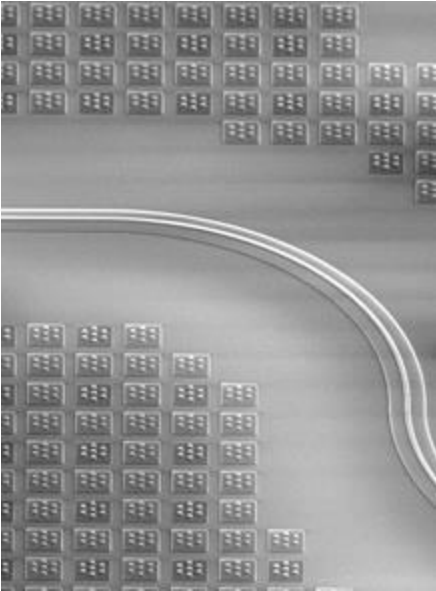
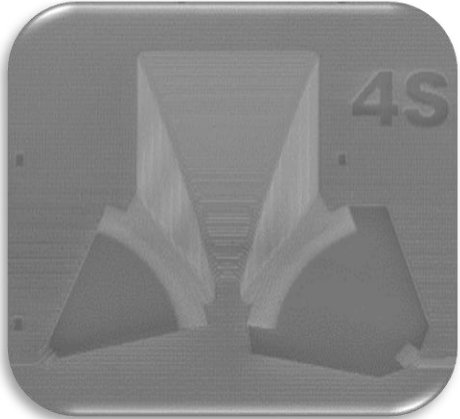
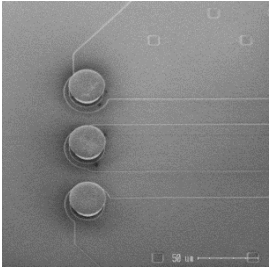
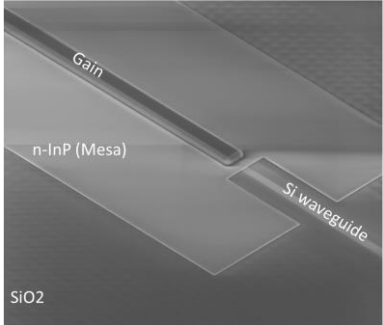
2017 O-Band MPW offer



2021 Scintil Spin-off

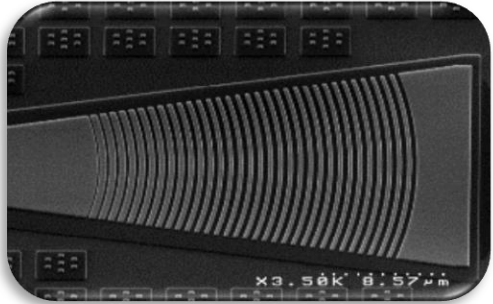
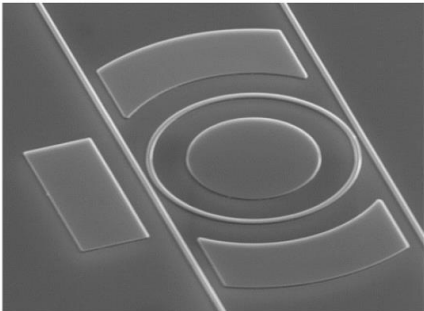
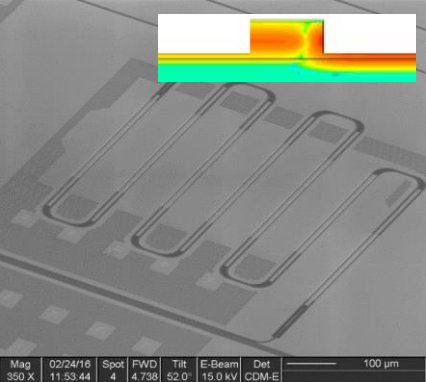
from I.P. Kaminow,
J. LT, 26,9,2008

SILICON PHOTONICS PLATFORM

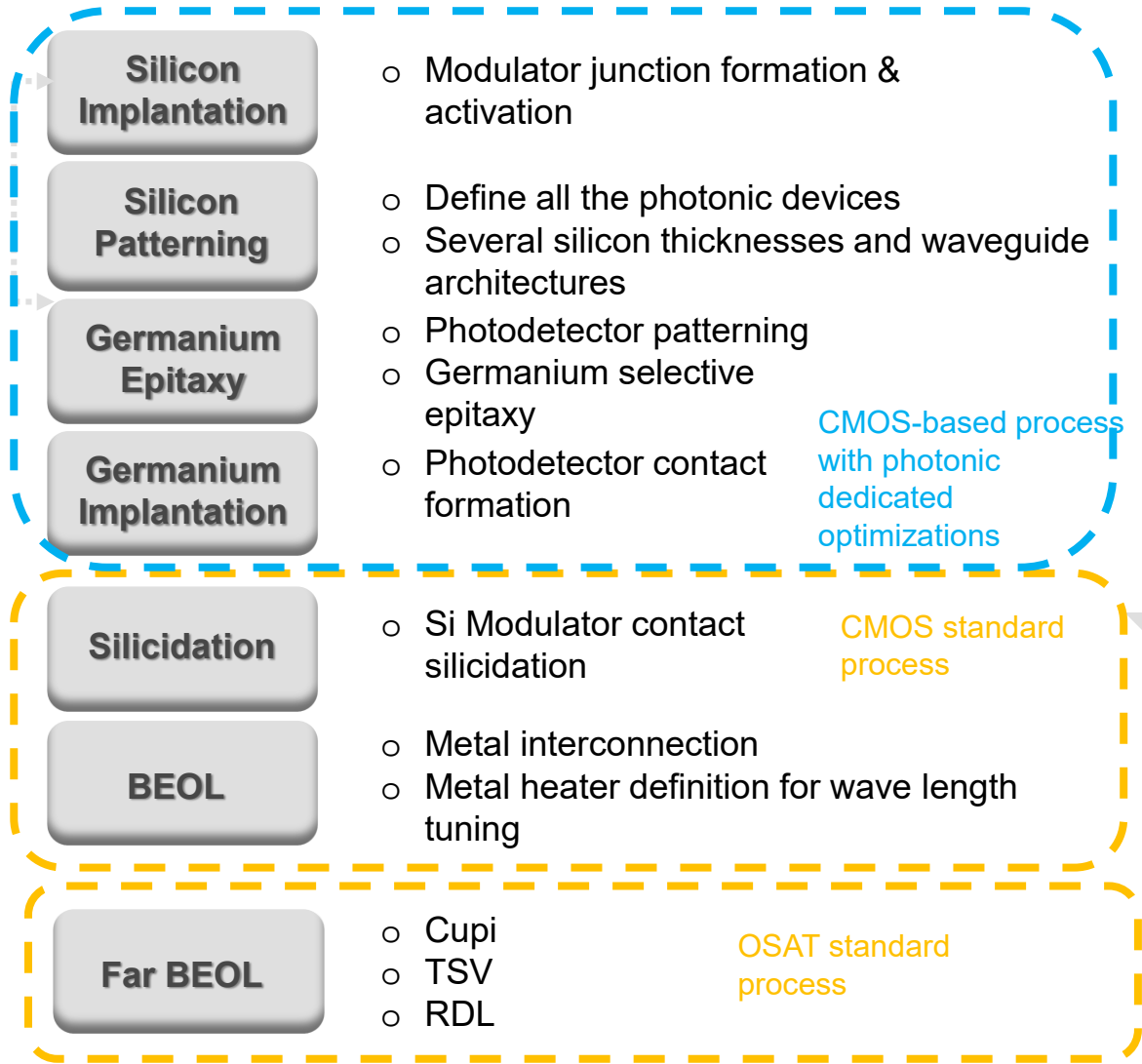


Modulator:
E to O conversion

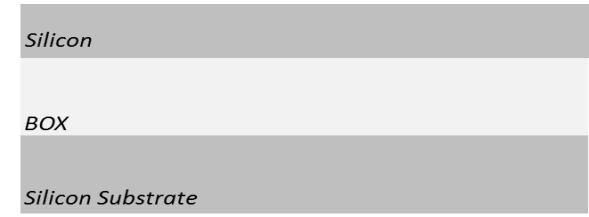
Multiplexer:
Signal combining



SILICON PHOTONICS : TECHNOLOGY OVERVIEW

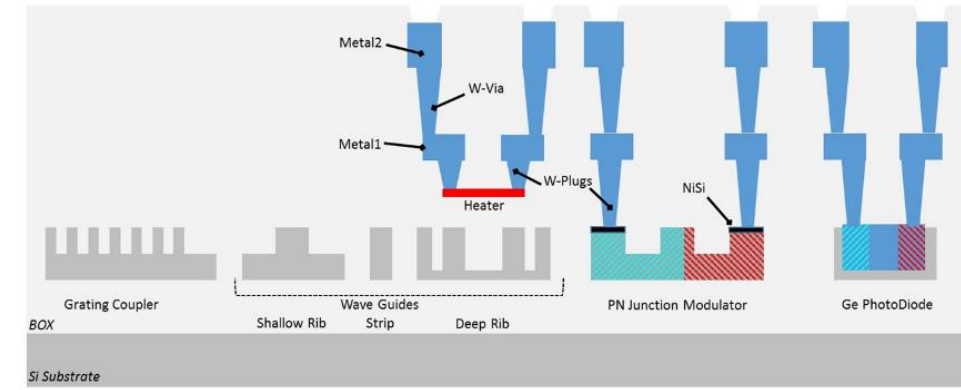


Silicon Photonic Process Flow



Silicon On Insulator (SOI) substrate : Ø8" or Ø12"

Schematic cross section of a silicon photonic circuit (Leti)

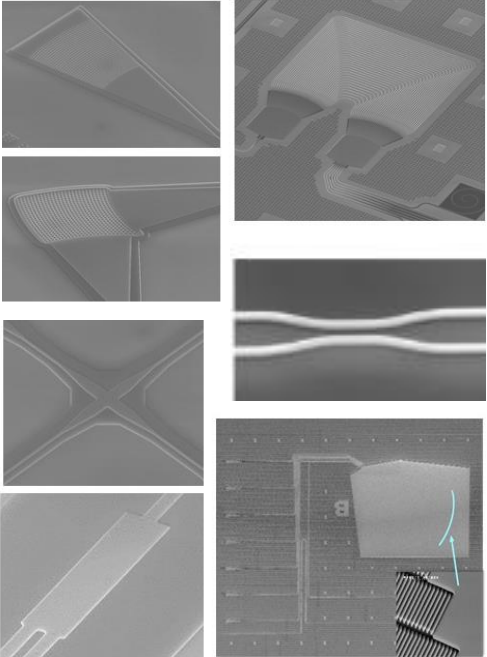


DEVICE LIBRARY AND PROCESS DESIGN KIT AVAILABLE



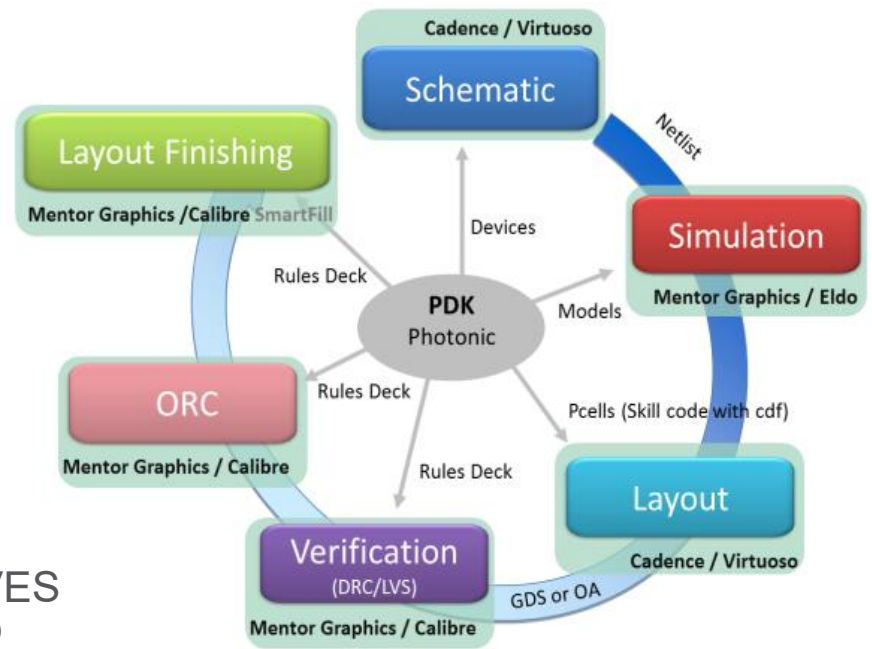
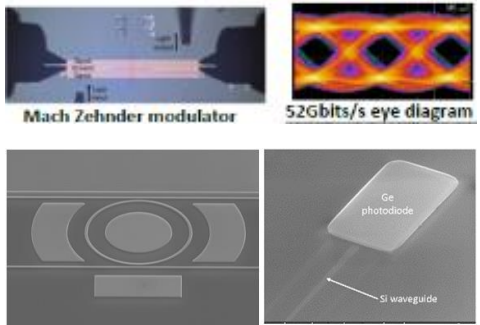
PASSIVES

O-BAND & C-BAND
 Rib, deep rib, strip, rib MM,
 bend strip, bend rib, bend
 deep rib, fiber grating
 coupler 1/2D, directional
 coupler, transitions, ring
 filter, MMI...



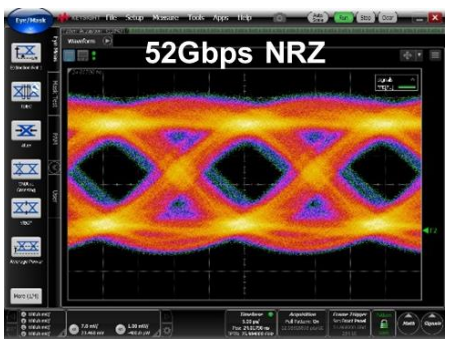
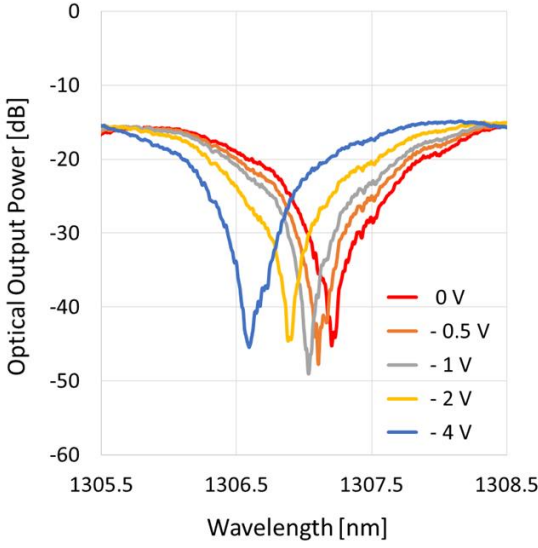
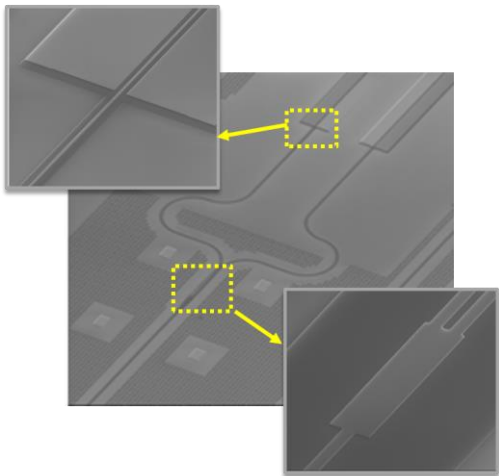
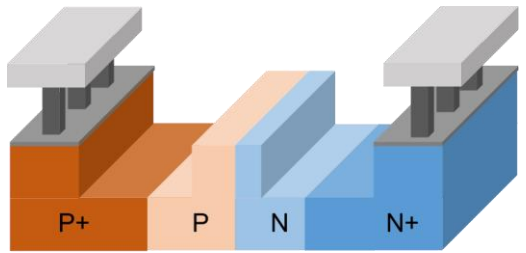
ACTIVES

O-BAND
 Mach-Zehnder Modulator,
 ring racetrack modulator,
 Ge photodiode PIN
 longitudinal



SILICON PHOTONICS PLATFORM

Carrier depletion in PN/PiN diode (reverse bias) for High Speed Modulation Section



Ge epitaxy in cavity for High Speed Ge PIN Photodiodes

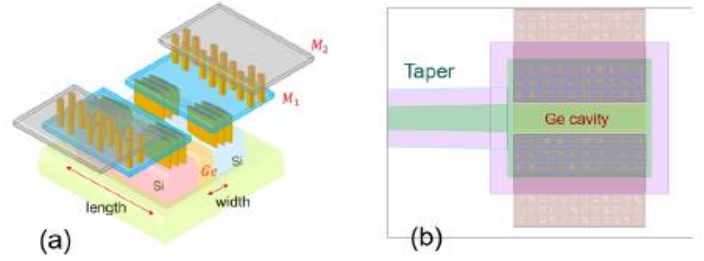


Figure 3. (a): Si/Ge/Si photodiode stack-up layers view. (b) Photo-diode planar view

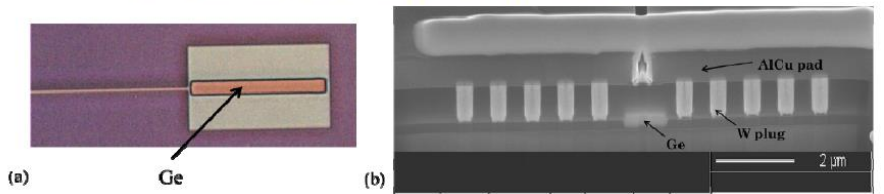
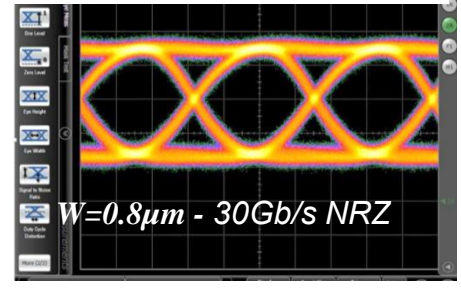


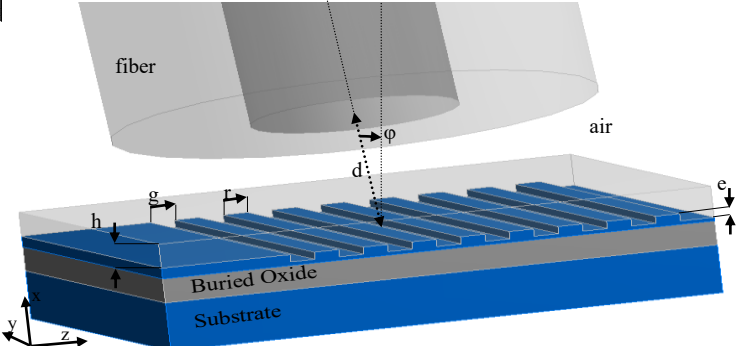
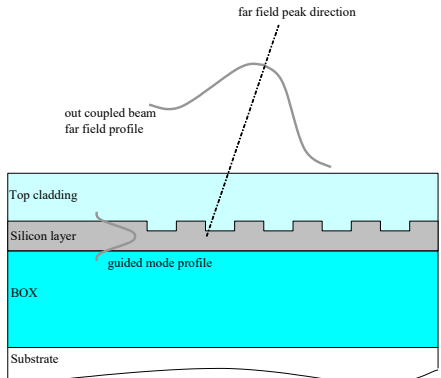
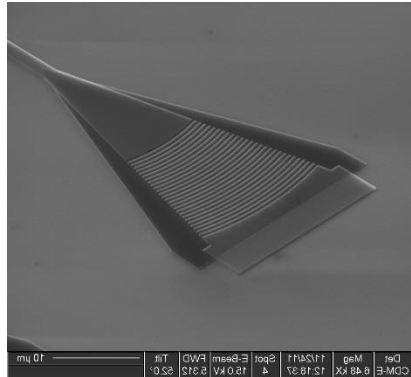
Fig. 3. (a) Top-view of a fabricated 1 μm wide Ge cavity after CMP. (b) Cross-sectional SEM image of a 1 μm wide Ge cavity photodiode.



Szelag B, et al. Optimization of 64Gbps O-band thin-rib PN junction. Mach-Zehnder Modulator fabricated on a 200mm silicon photonics platform. SSDM 2018.

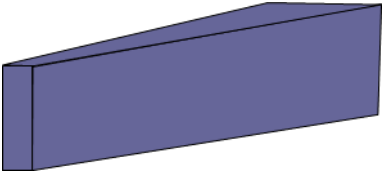
H. Zegmout *et al.*, « High speed integrated waveguide lateral Si/Ge/Si photodiodes with optimized transit time », 2020, vol. 11285. EPS Workshop| Stéphane Bernabé | 21.10.21| 17

COUPLING STRUCTURES

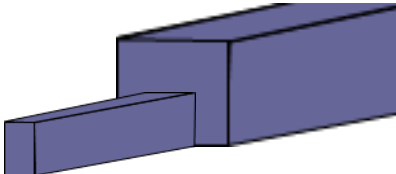


Vertical Grating coupler

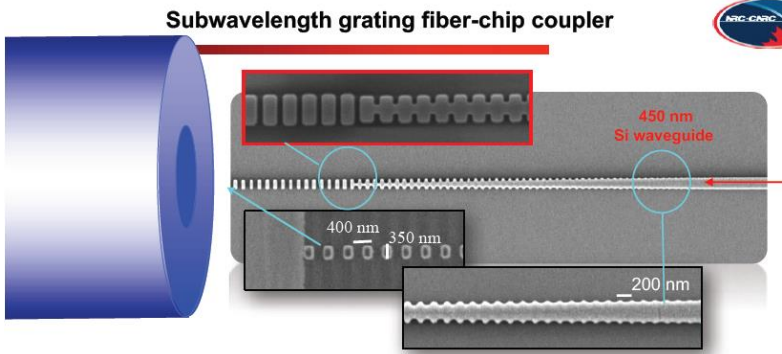
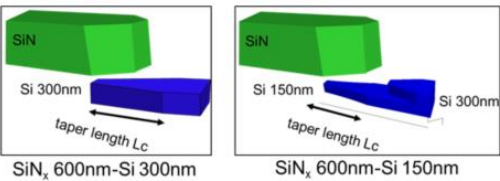
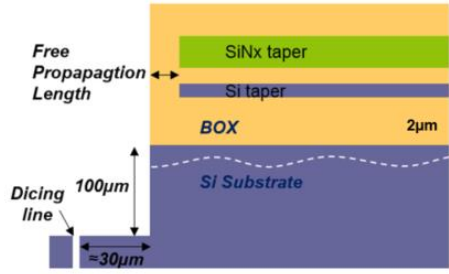
- 50% to 80% efficiency for 1 polarization
- Ideal for waferscale testing
- Limited bandwidth
- Alignment tolerance: +/- 2 μm (well fitting mode size)



Si 300nm taper



Si 150nm/300nm taper



Note: Well designed adiabatic transitions are important !

Adiabatic taper coupler for Edge Coupling

- Broadband
- Small mode size (3 μm diameter)

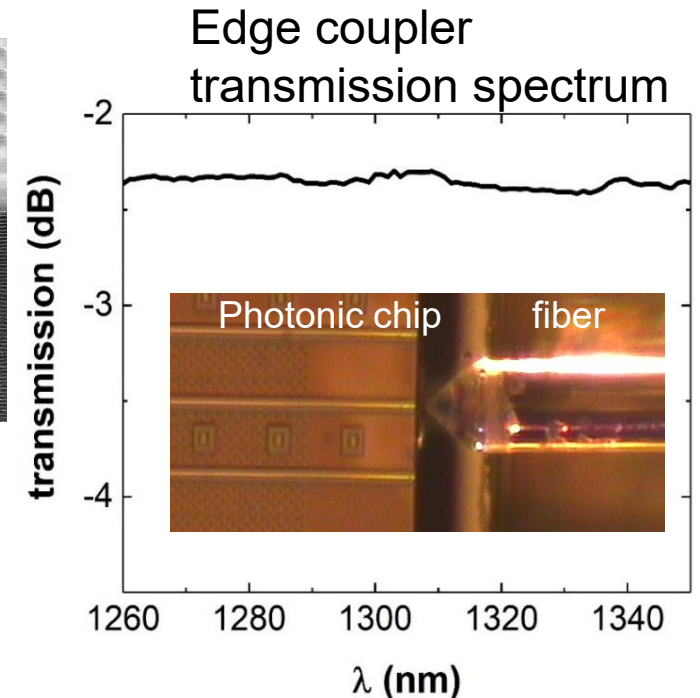
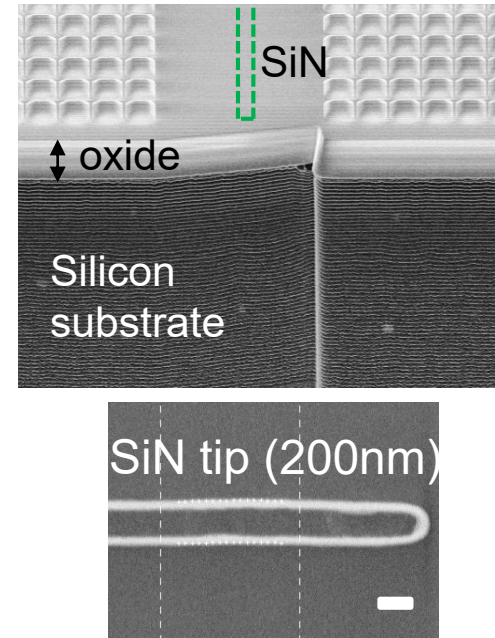
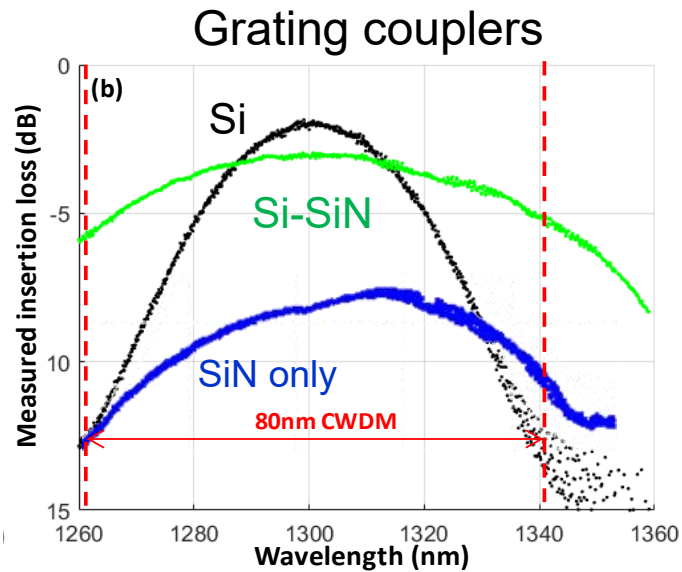
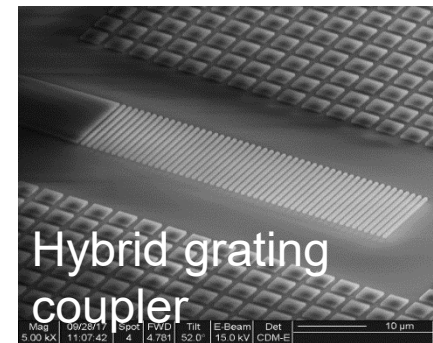
SiN-Si hybrid grating coupler

- 2-layers grating SiN-Si
- 2.8 dB insertion loss
- -1dB BW ~ 50nm

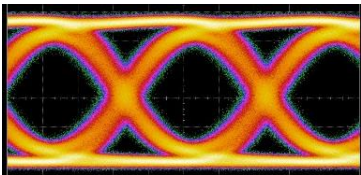
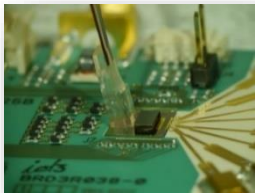
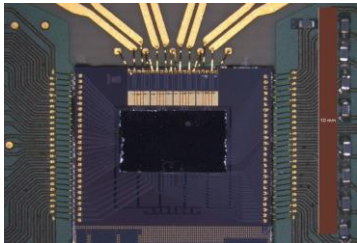
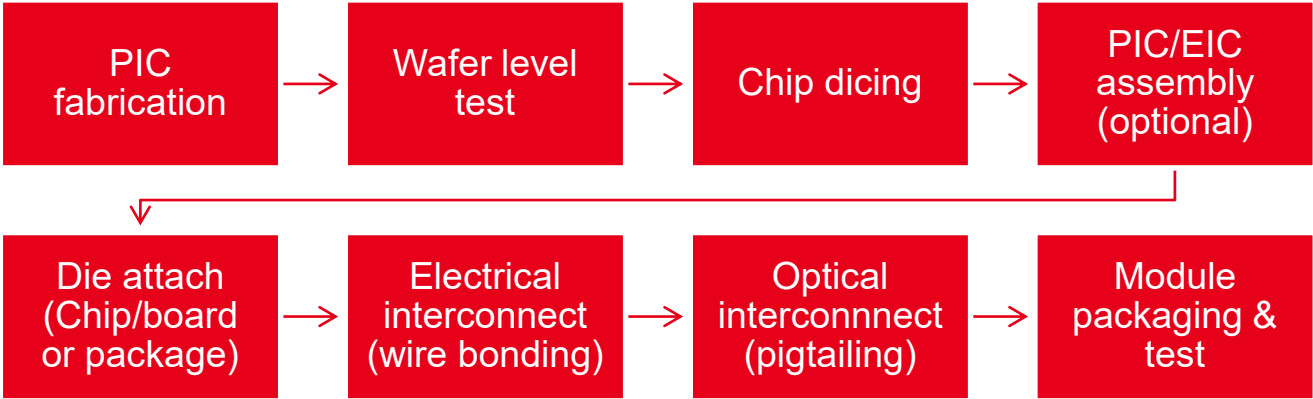
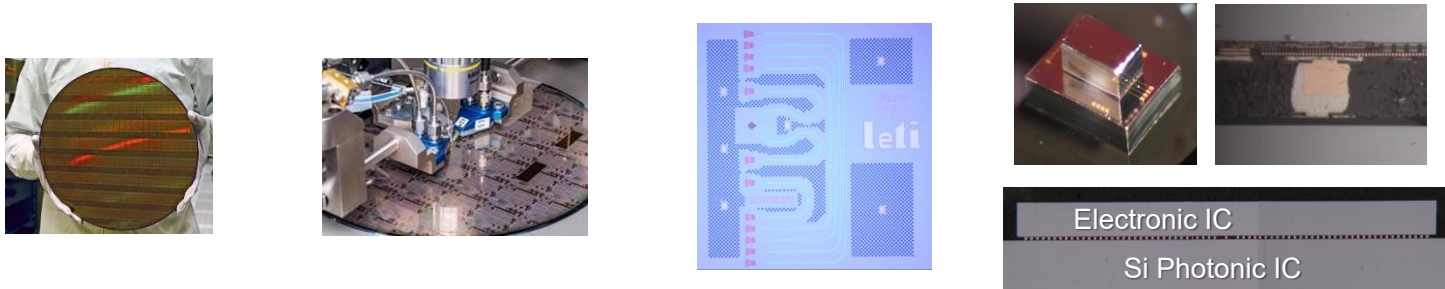
→ CWDM components wafer level testing (broadband)

Edge coupler with SiN taper

- Lensed fiber : MFD = 2.5 μ m
- SiN inverse taper
- Deep trench by dry etching
- Coupler insertion loss : < **2.4dB** (O-band)
- For CWDM modules

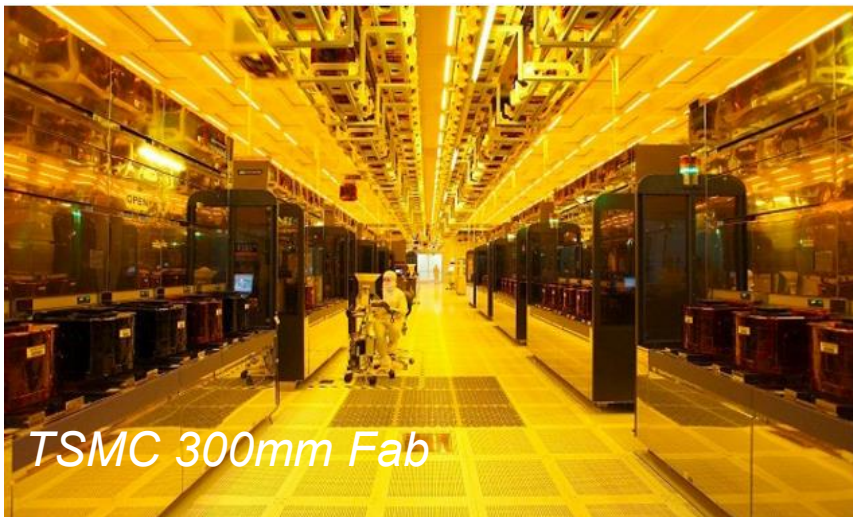
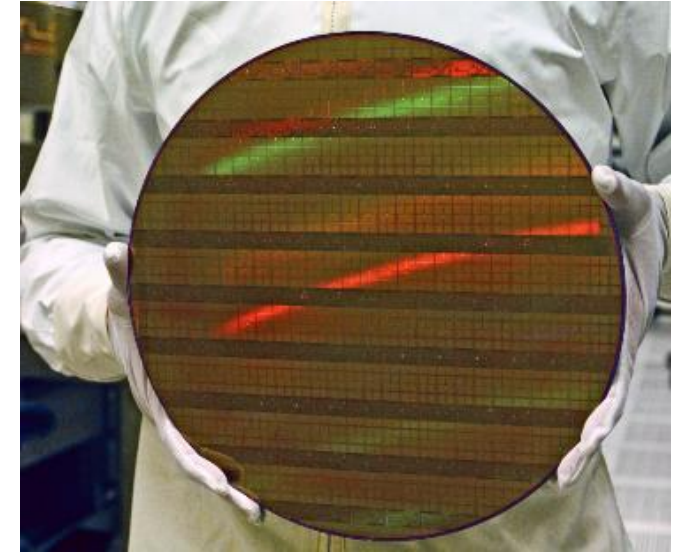


SILICON PHOTONICS MODULE ASSEMBLY FLOW



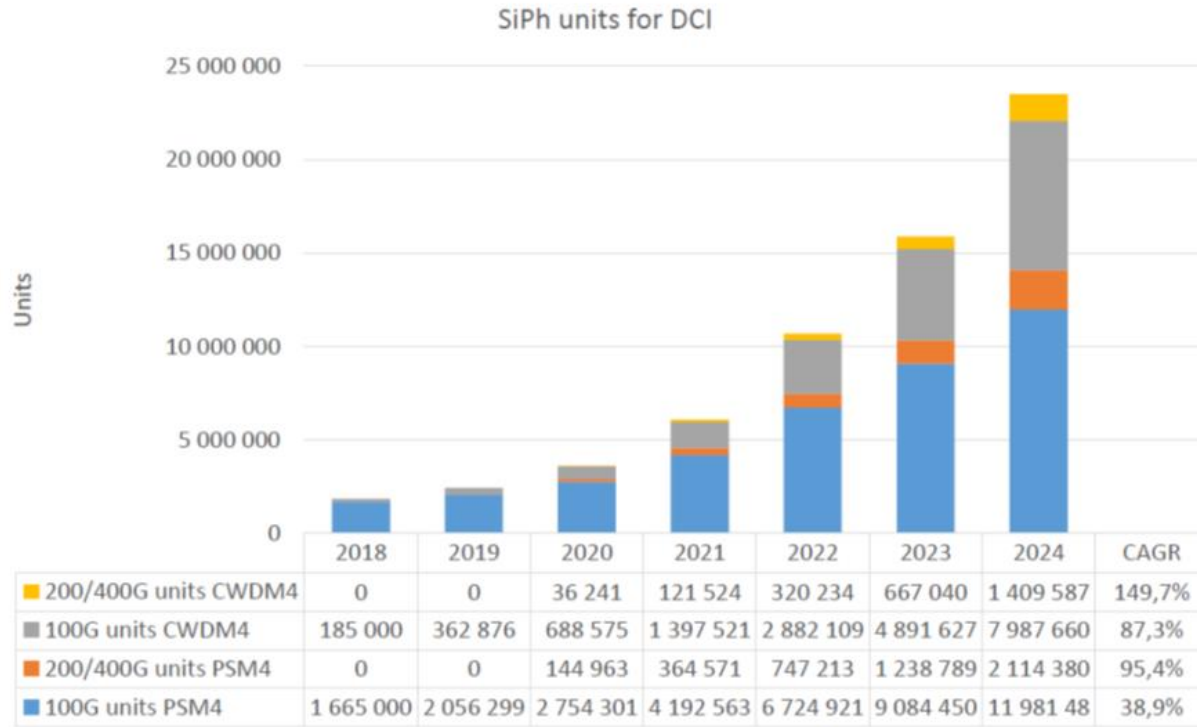
SILICON PHOTONICS : ADVANTAGES

- Small devices thanks to high index contrast between Silicon and oxide
- Integrated photonic device onto silicon, manufactured in a CMOS fab, enables low cost mass production
- Scalability to increase bit rate per channel : wavelength multiplexing, advanced modulation format
- Low-latency : architecture with unified switched photonic network
- High speed end-to-end network paths
- Wafer scale testing
- Solving electrical interconnect limits in Data centers, Supercomputers and ICs with higher capacity, lower cost optical interconnects



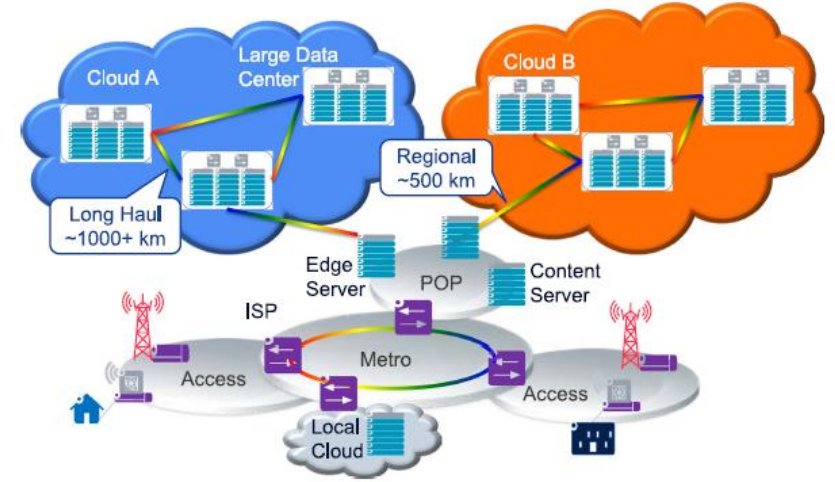
Intel Transceiver

ROADMAP / MARKET TRENDS

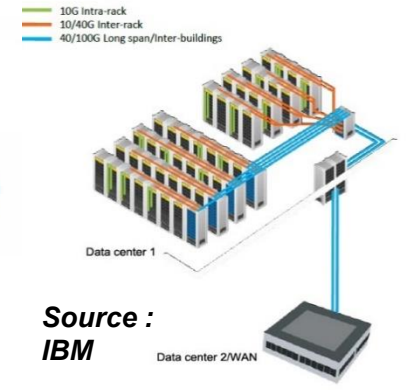
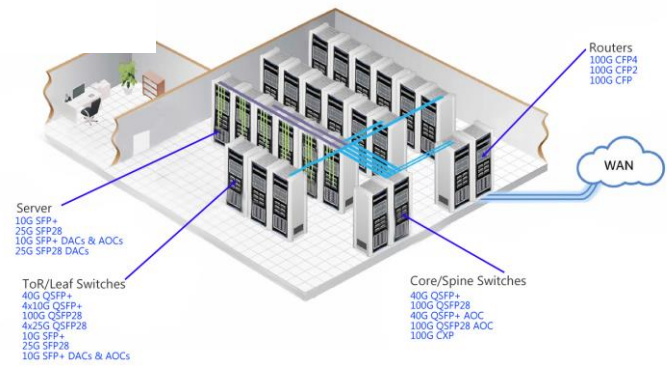


Source: Yole

- 400G is widepreading
- Increasing size of DCs
- <1\$ / Gbps required
- Ethernet transceiver market is expecting to reach 43Munits by 2025



Source : ADVA



APPLICATIONS BEYOND TELECOM & DATACOM

3D sensing and LIDAR
Automotive, robot, drone and smartphone

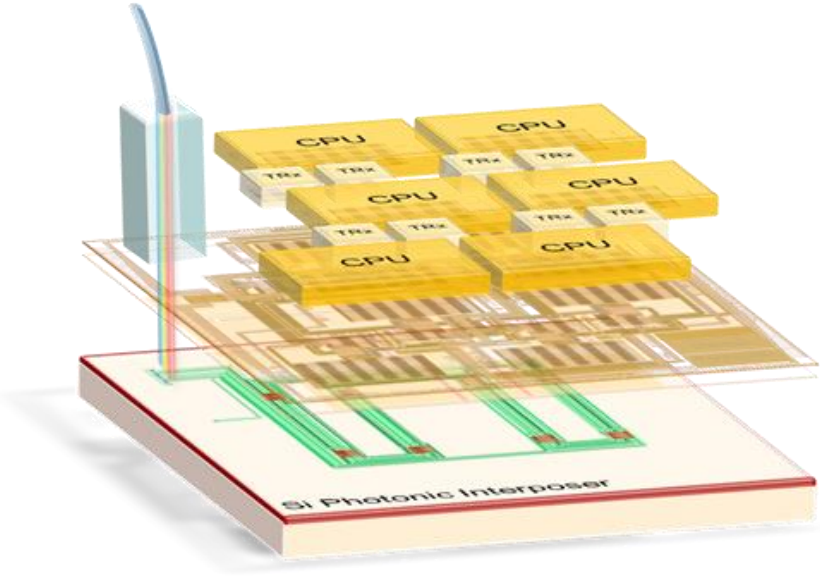
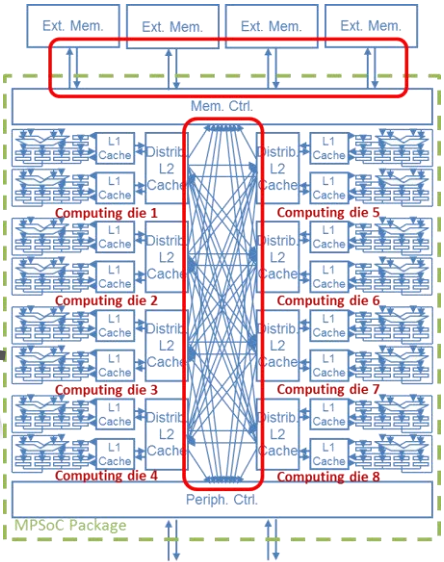
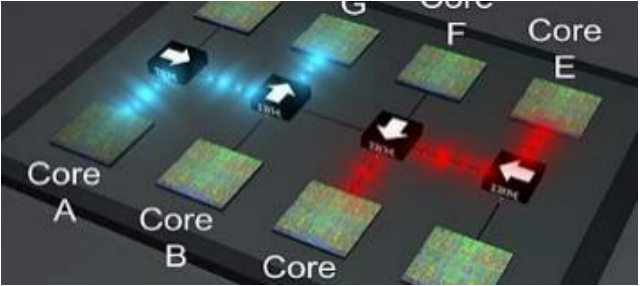
Alternative computing
Neuromorphic, reservoir and quantum

Computer communication
High Performance Computing, ONoC

OPTICAL NETWORK ON CHIP

Photonic assisted processor

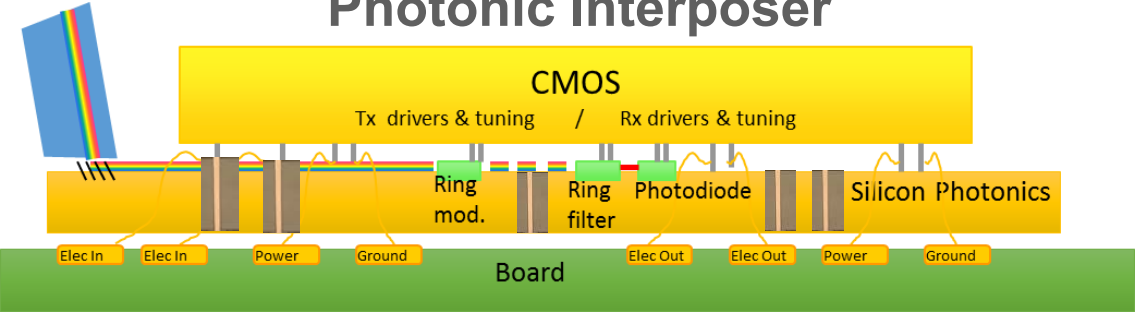
- Multi-cores bottlenecks
- Chiplet approach
- Manycore architectures
- Known Good Die sorting



Photonic Interposer

with increasing maturity of silicon photonic platforms and compatibility with face-to-face die hybridization, it is now possible to consider the implementation of **optical network-on-chip (ONoC) topologies** on silicon photonic interposers to go beyond the scalability limitations of active CMOS interposers.

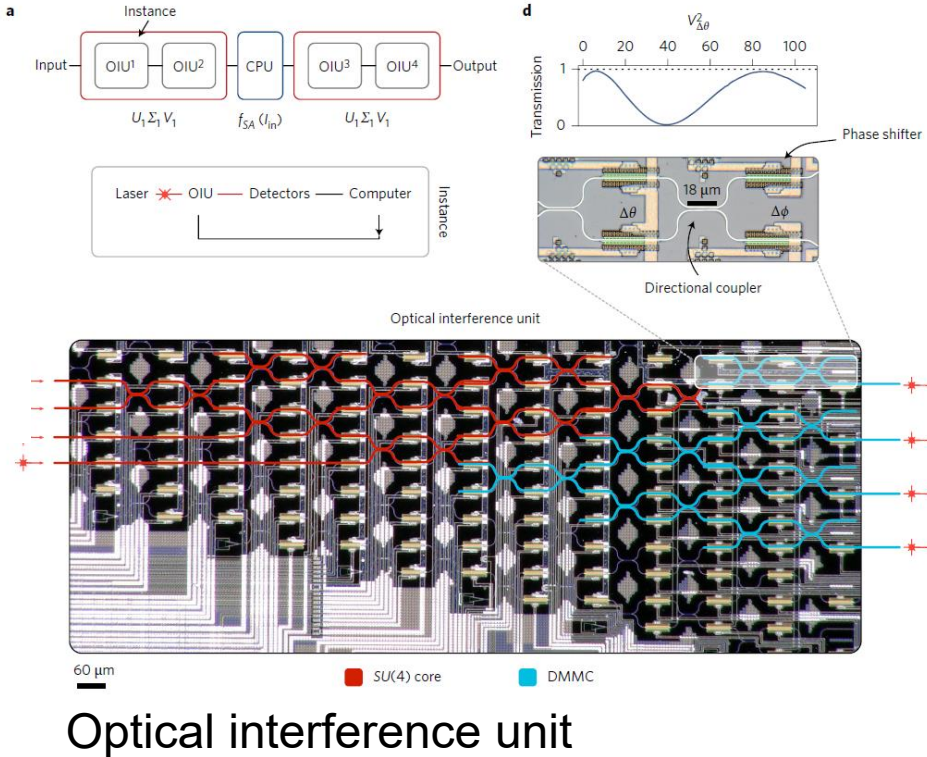
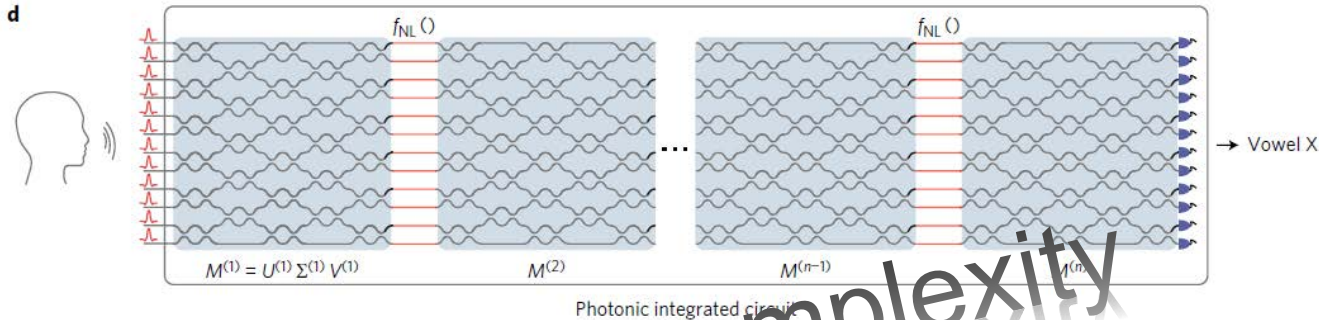
Photonic Interposer





Deep learning with coherent nanophotonic circuits

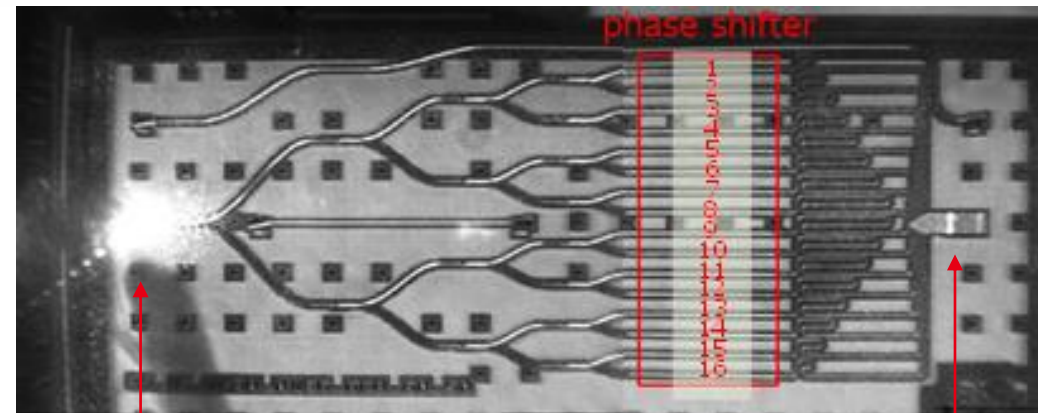
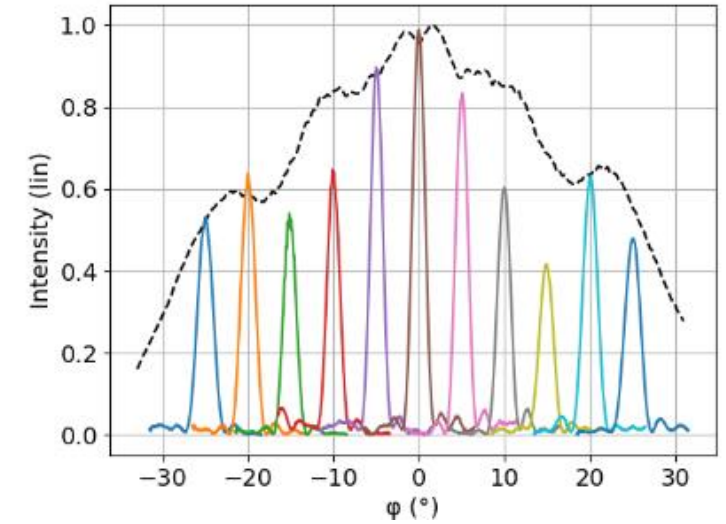
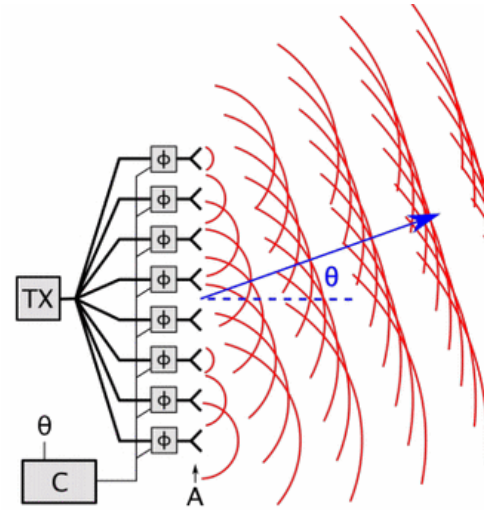
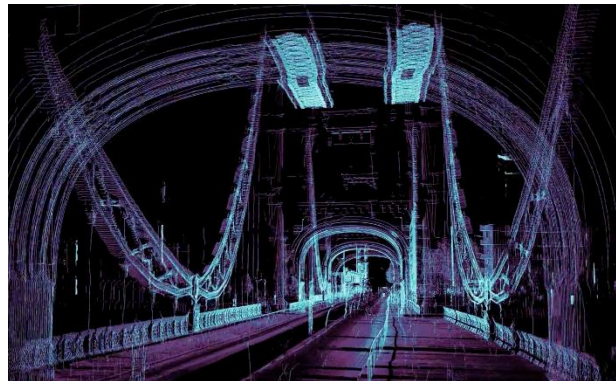
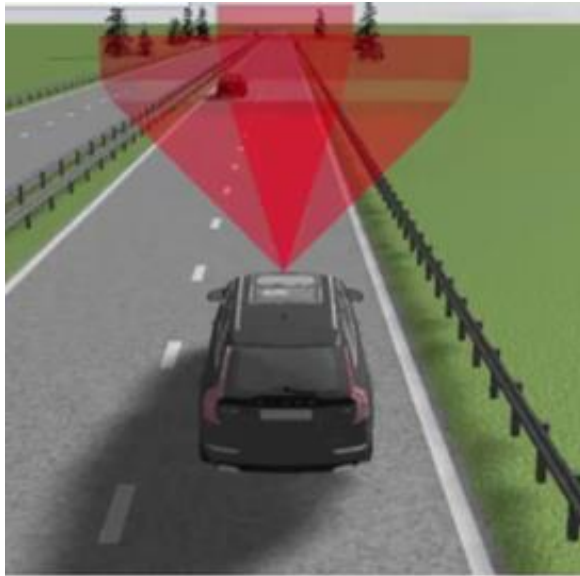
Yichen Shen^{1*}†, Nicholas C. Harris^{1*}†, Scott Skirlo¹, Mihika Prabhu¹, Tom Baehr-Jones², Michael Hochberg², Xin Sun³, Shijie Zhao⁴, Hugo Larochelle⁵, Dirk Englund¹ and Marin Soljačić¹



Increased complexity
=> Packaging challenges

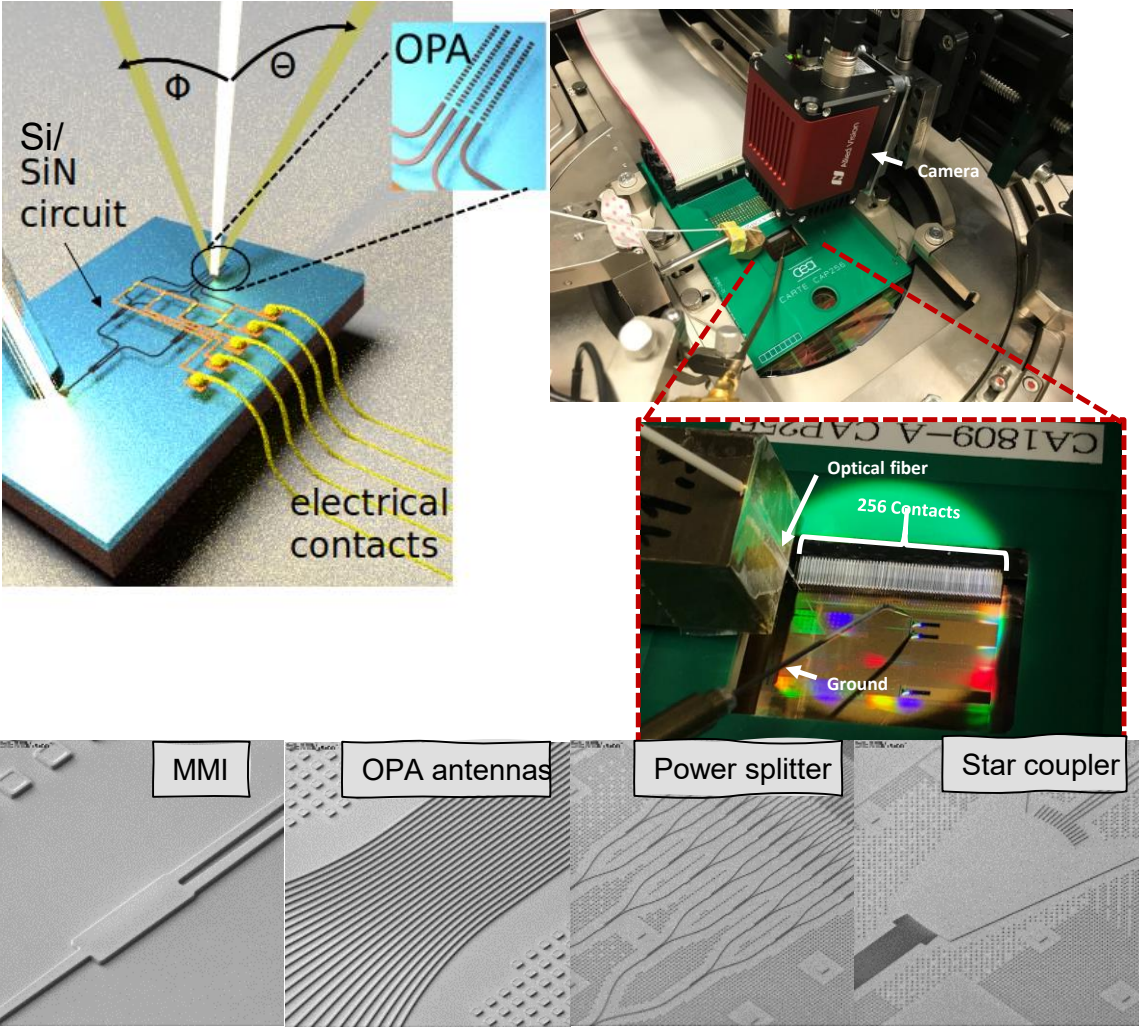
OPTICAL PHASED ARRAY LIDARS

- Optical Beam steering for automobiles

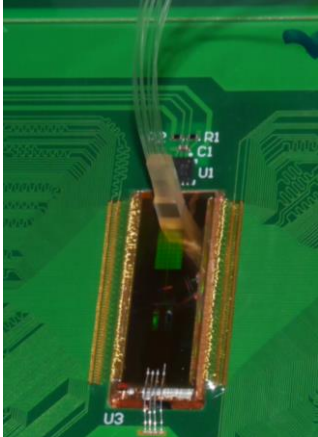


OPTICAL PHASED ARRAY LIDARS

- Development of Optical Phased Arrays for LIDAR systems and other applications
 - Application specific design of photonic components for 500-1000nm (SiN) or 1250-1600nm (Si or SiN).
 - Relies on thermo optic effect applied to waveguides
 - Co-design of photonic circuit and ASIC for hybrid integration of driver electronics.
 - Packaging of demonstrators

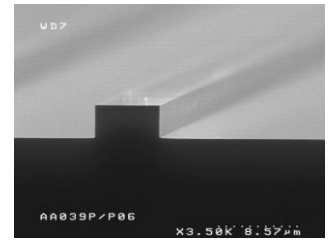
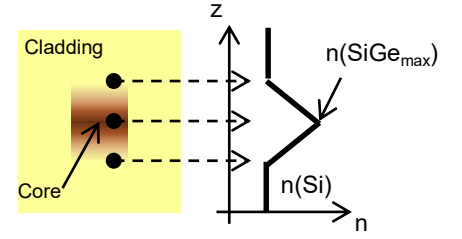
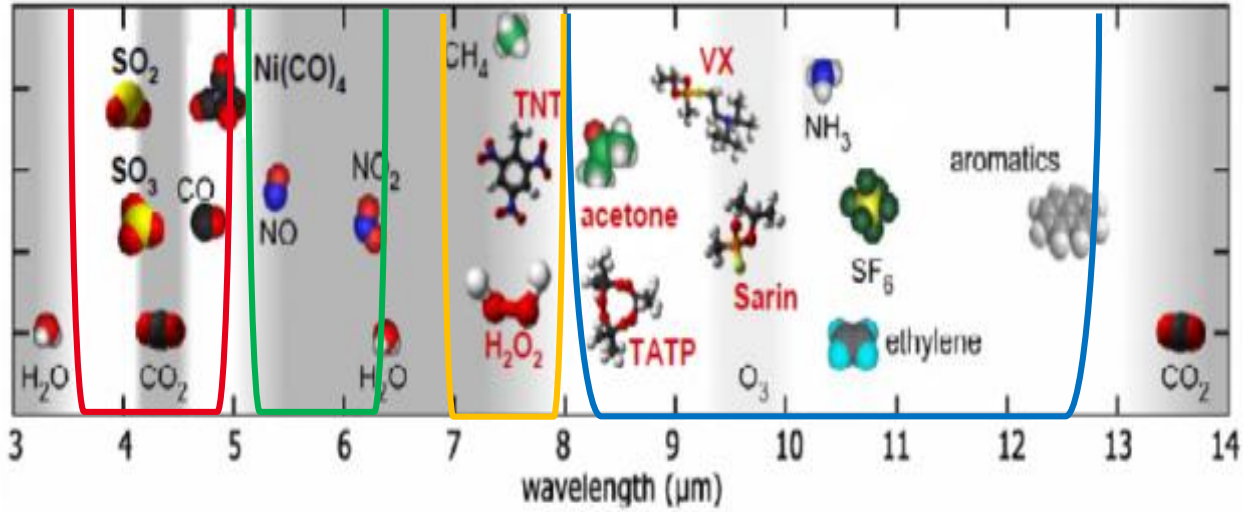


Packaging challenges

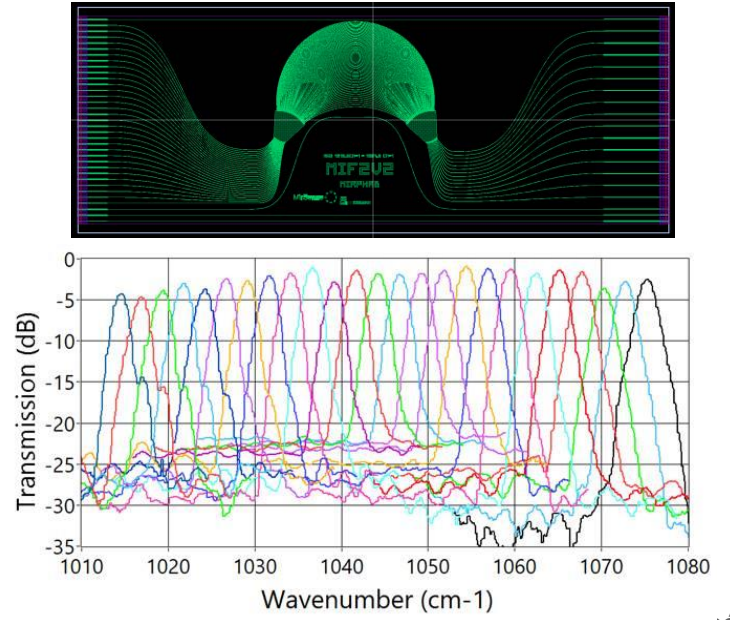
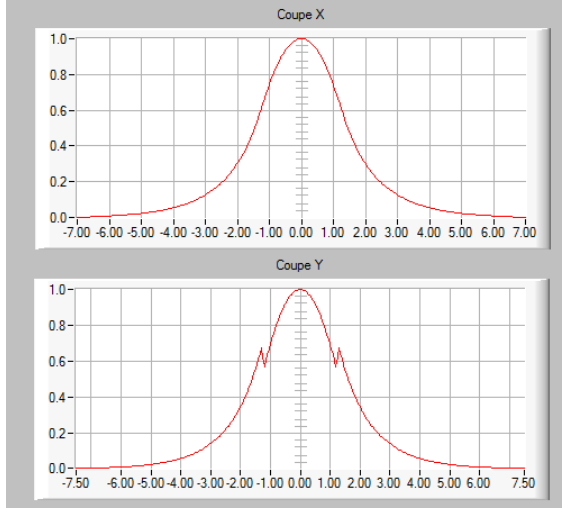


N. A. Tyler *et al.*, "SiN integrated optical phased arrays for two-dimensional beam steering at a single near-infrared wavelength," *Optics Express*, 2019
 S. Guerber *et al.*, "Development, calibration and characterization of silicon photonics based optical phased arrays," *Smart Photonic and Optoelectronic Integrated Circuits XXIII* 2021.

GAS SENSORS

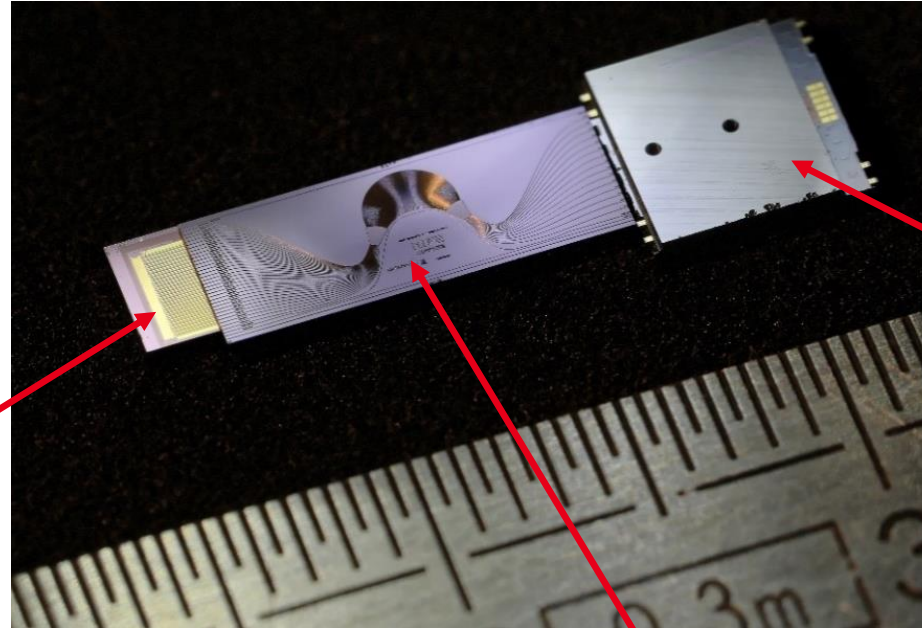


- **Single Mode waveguide:**
 - Core: Ge (section: 2.5 x 2.5 μm^2)
 - Cladding: SiGe
- **Characteristics FEM simulations:**
 - TM mode @ 8.7 μm
 - Mode size at (1% of max intensity) = 5.4 μm horizontal, 5.6 μm vertical
 - Minimum cladding of 6 μm SiGe around the Ge core



GAS SENSORS

Challenge: Combine source optics and detection on the same chip



Array Quantum Cascade
Lasers on Si

***Multigas detection
enabler***

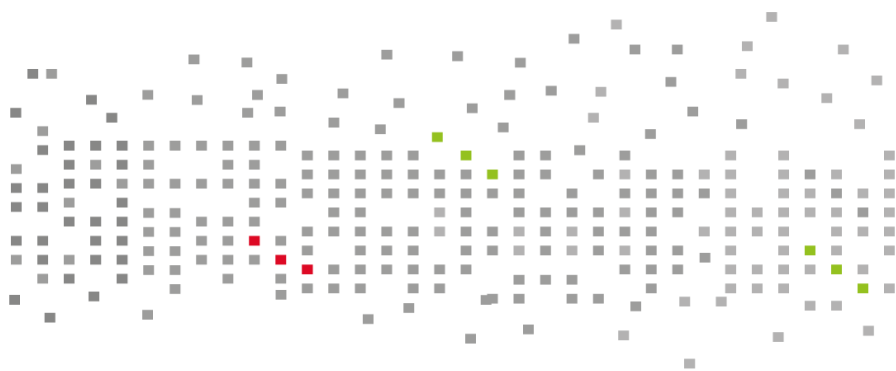
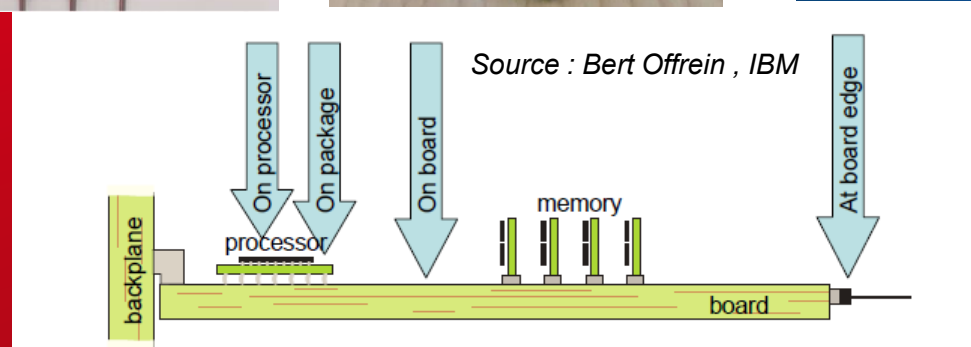
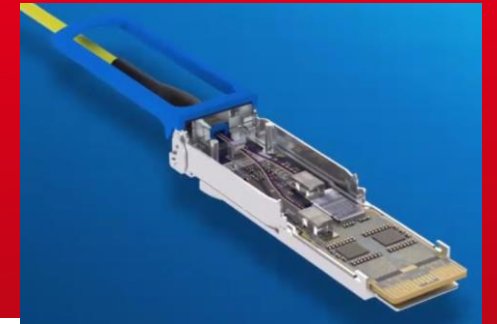
Photonics Integrated Circuit
Beam Combiner

***Replace costly and
fragile discrete optics***

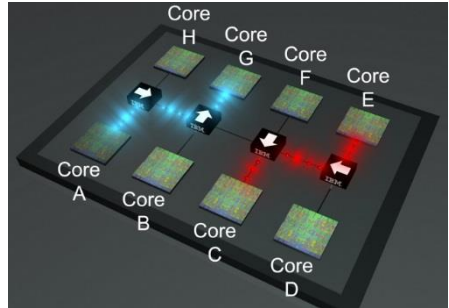
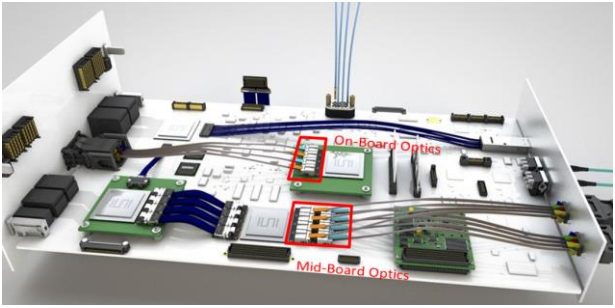
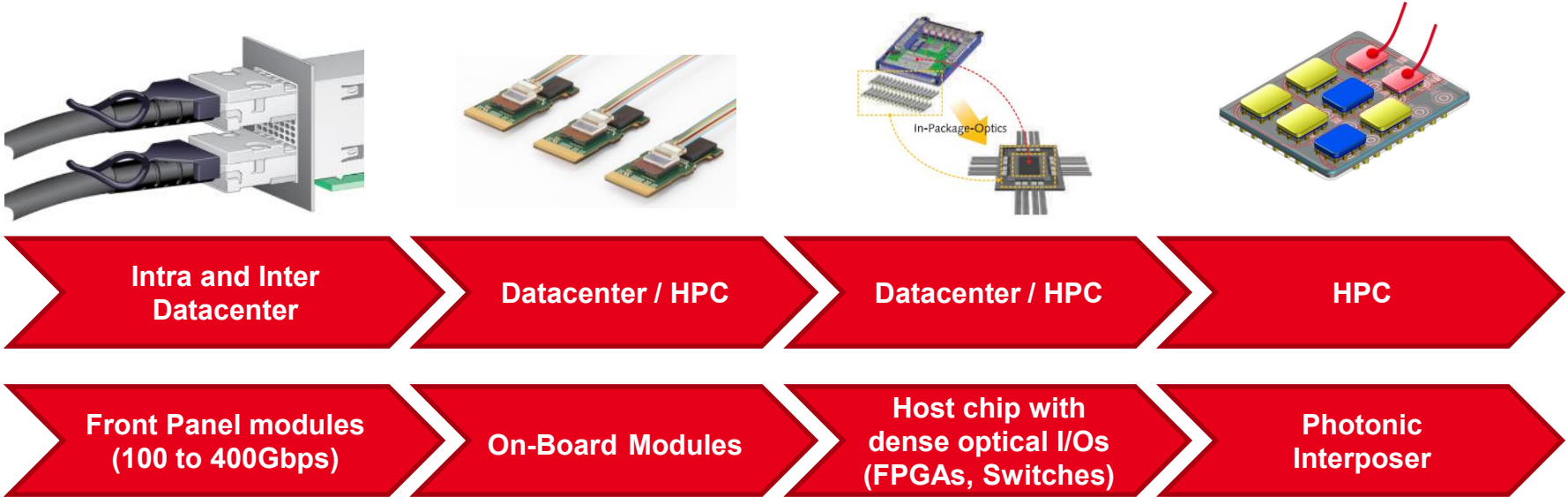
μ -PA: gas sensing cell
with MEMS μ Phone

***Replace bulky
multipass cells***

INTEGRATION CHALLENGES



ROADMAP : FROM RACK INTERCONNECTS TO NETWORK ON CHIPS

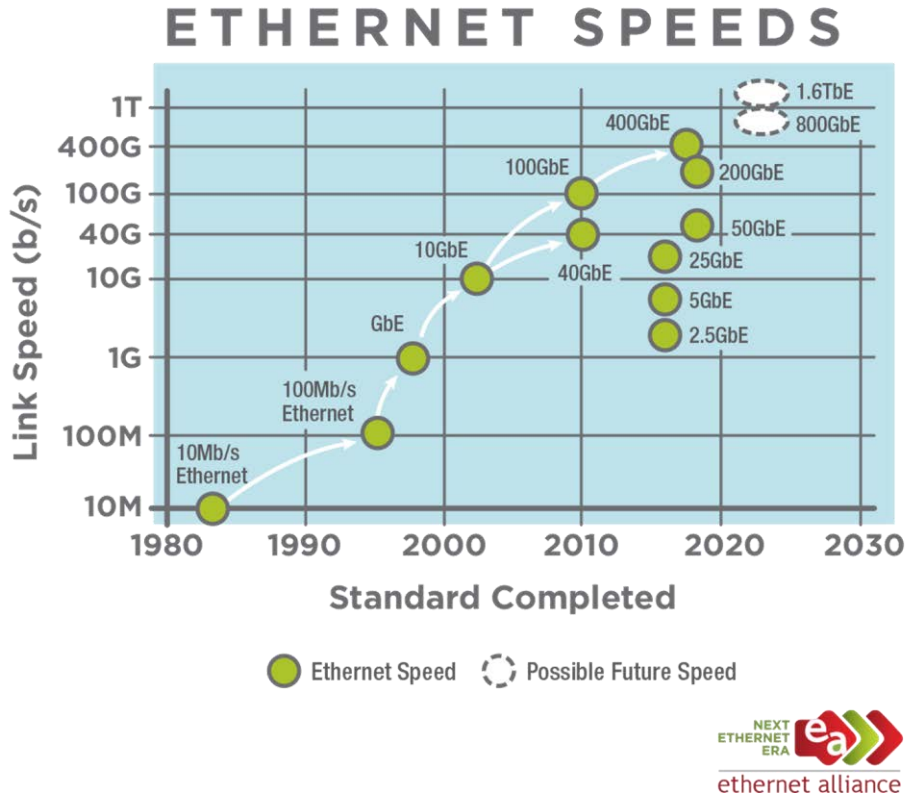


Review

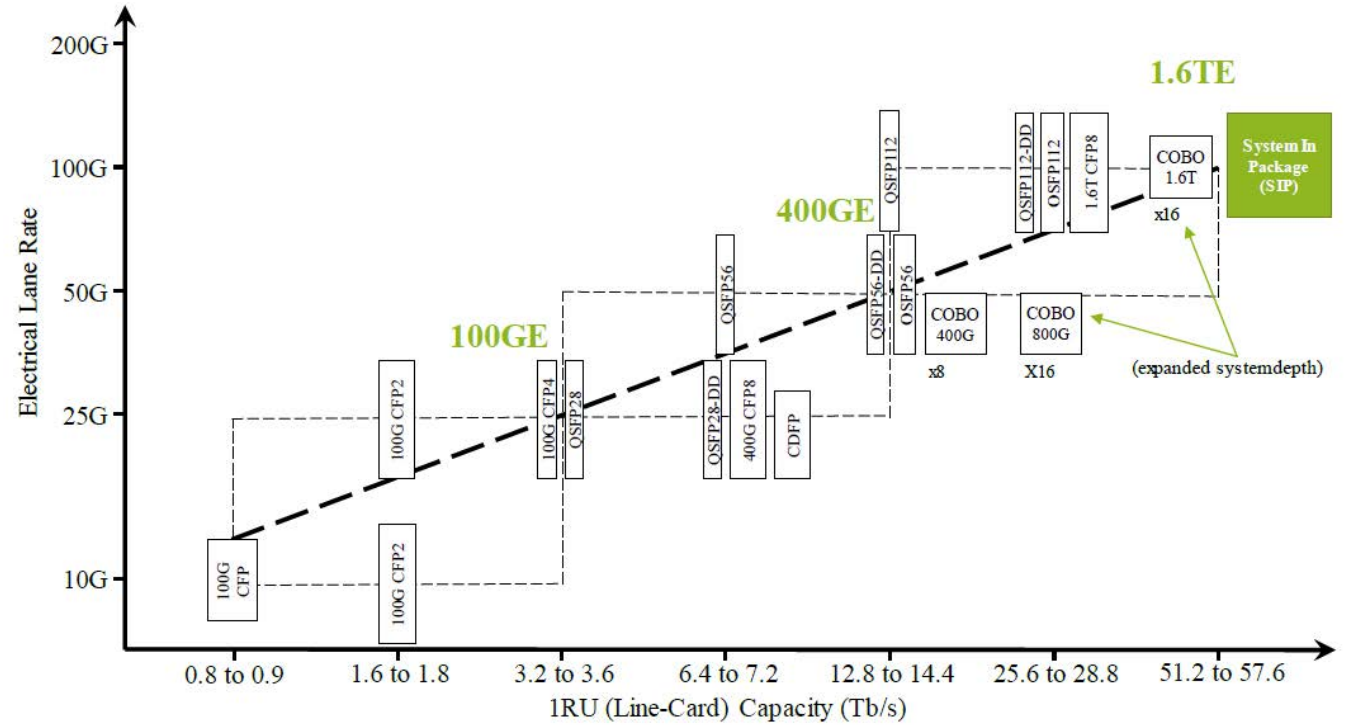
Silicon photonics for terabit/s communication in data centers and exascale computers

S. Bernabé^a, Q. Wilmart^a, K. Hasharoni^b, K. Hassan^{a,e}, Y. Thonnart^a, P. Tissier^d, Y. Désières^a, S. Olivier^a, T. Tekin^c, B. Szelag^a

^a Univ. Grenoble Alpes, CEA LETI, Minatec Campus, F38054 Grenoble, France
^b DustPhotonics, 11 Tzela Hahar, Modiin, Israel
^c Fraunhofer IZM, Gustav-Meyer-Allee 25, 13355 Berlin, Germany
^d ST Microelectronics, Crolles, France
^e III-V Lab, Joint Lab of Nokia, Thales & CEA, 1 A. Fresnel, 91767 Palaiseau, France



- 100G proliferating
- 400G ramping up



- Next step, 800G and 1.6T
- Road >400G includes COBO and co-packaging

- Enable 2D use of the board
(no more front panel limitation)
- >100Gpbs data rate
- Can be used for intra-rack or intra-board applications
- Optical modules integrated on PCB or on BGA package, near the host chip (processors or FPGA)
- RF lines are shorter and the whole motherboard surface can be used to provide host chips with E/O transceivers
- Already available with VCSEL embedded (e.g. Avago, TE...)
- **COBO** Initiative defining the RF interface

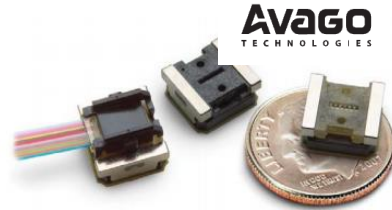
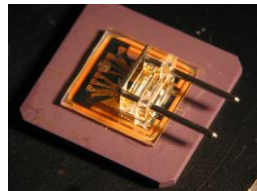
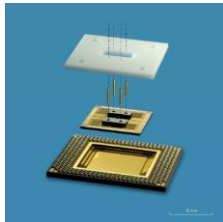
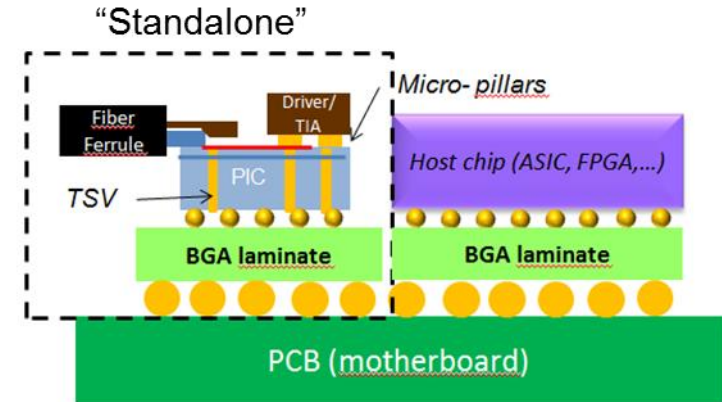
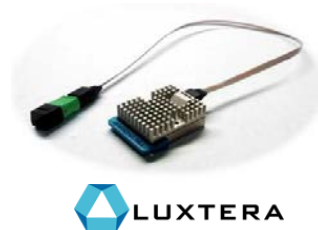
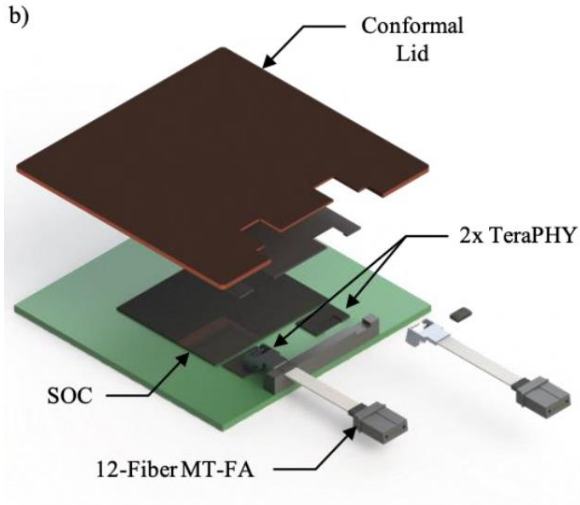


Figure 4. Mid-board optics modules shown here provide the key to a high-density interface.

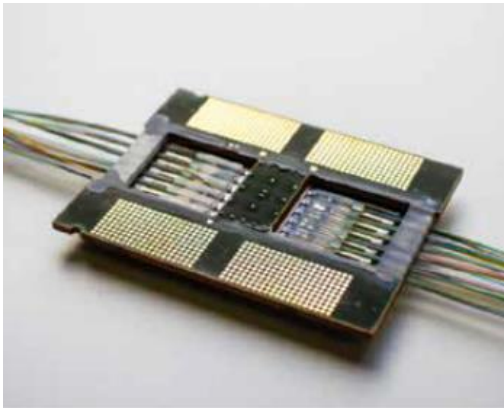
Tyco, 2012



NEXT STEP : SYSTEM IN PACKAGE REQUIREMENTS

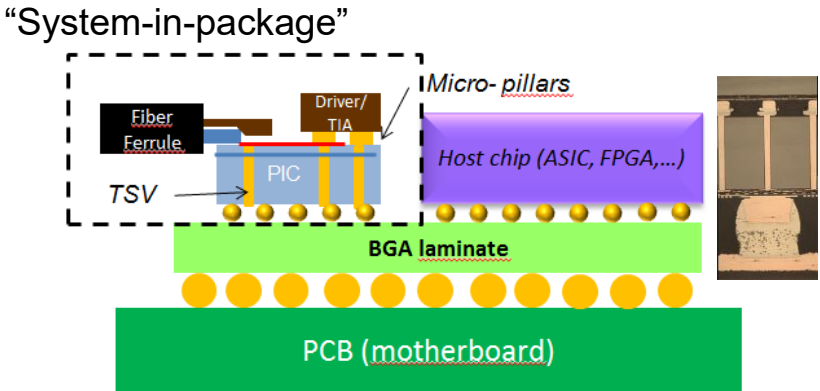


Ayar Labs' TeraPHY



Rockley Photonics' OptoASIC

- To provide 25 Tbps switches (and 50 Tbps) with Photonic Transceiver
- Low footprint, high density modulators needed
- TSV may improve integration
- Reflow compatible connectors needed
- Laser integration management
- Many new module architectures from Start ups & RTOs



FIBER COUPLING

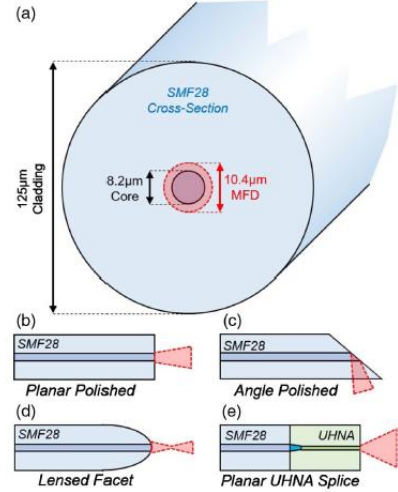
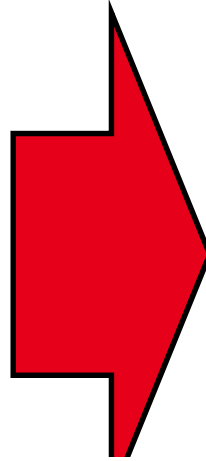
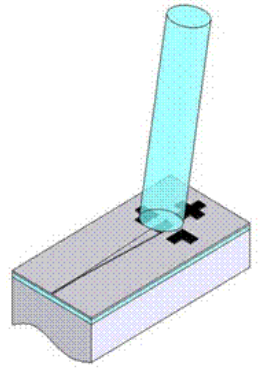
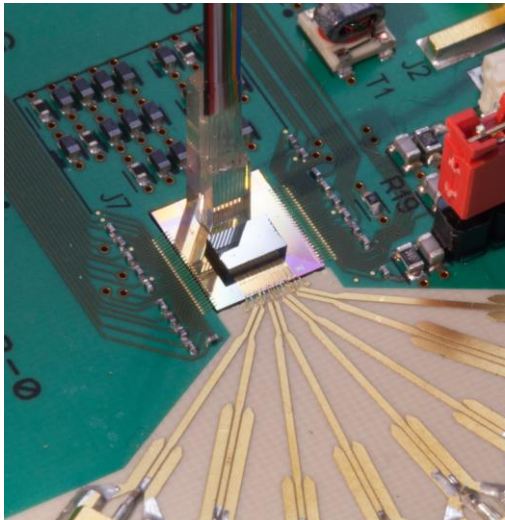
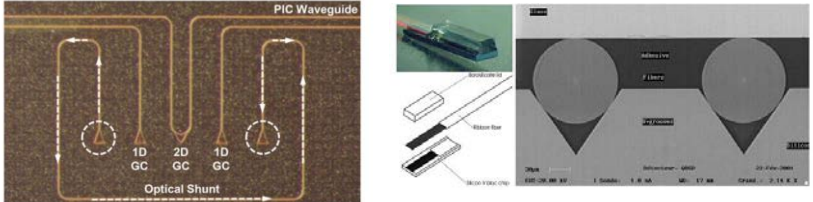


Fig. 2. (a) Cross-section schematic of an SMF28 fiber, showing the 8.2 μm fiber core centered in the cladding layer, wave-guiding the 10.4 μm MFD 1.55 μm mode. Side view schematics of (b) planar polished, (c) angle polished, and (d) lensed SMF28. (e) Schematic of UHNA-to-SMF28 splicing, showing the thermally expanded adiabatic taper. The (b), (d), and (e) geometries are commonly used for edge coupling, while the (c) geometry is preferred for grating coupling.

Passive alignment
 Easy to package
 Broadband
 Small Form Factor

WANTED !

- Active alignment
- Not pluggable
- Not broadband

O. Castany, ESTC 2016 ;
 Jun Su Lee, IEEE JSTQE 22,6, 2016

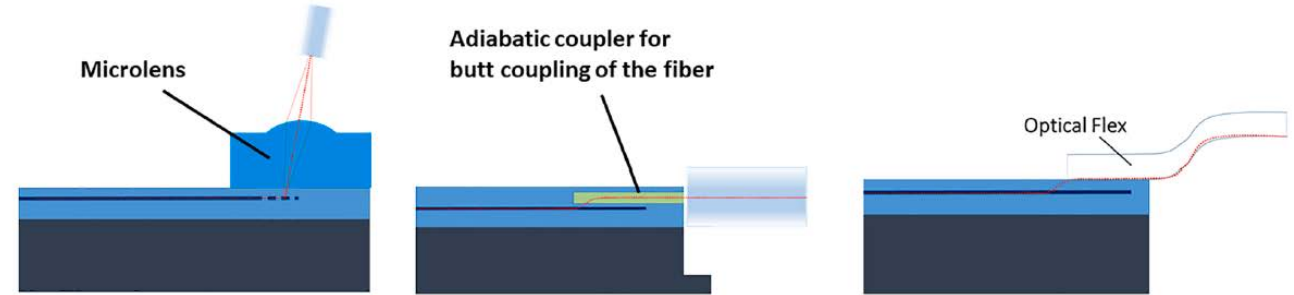
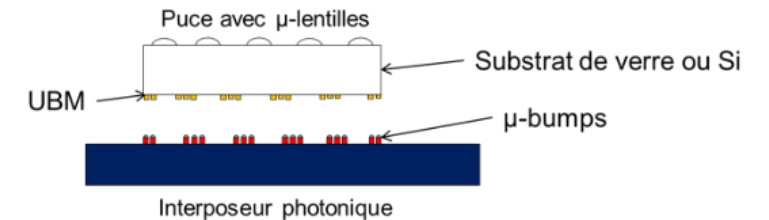
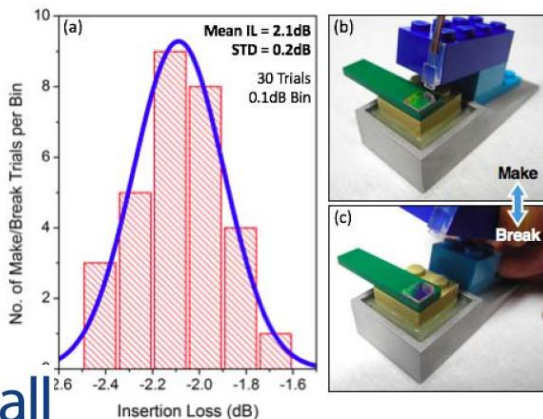
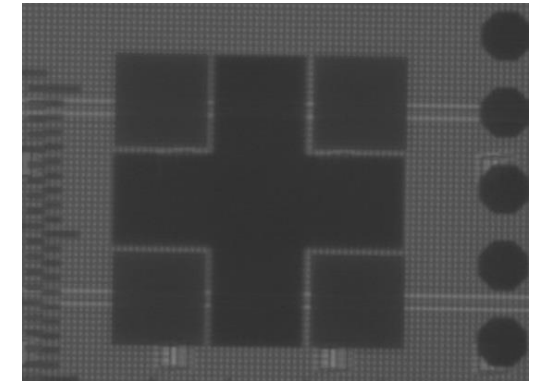
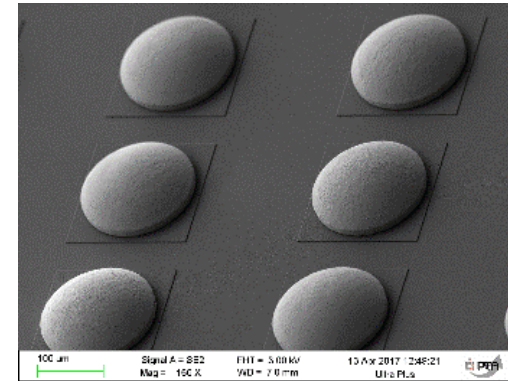
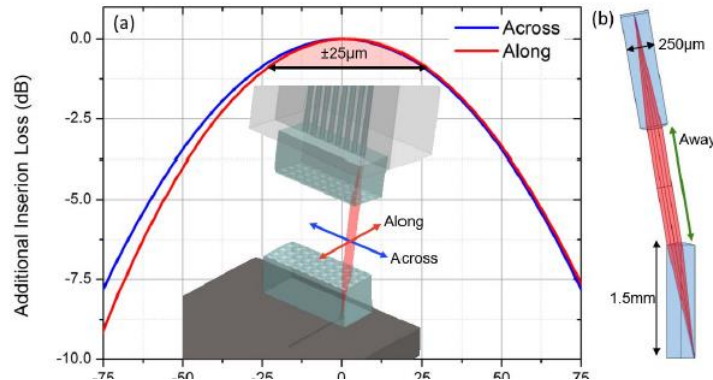
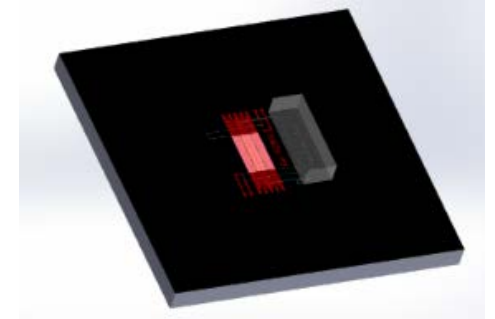
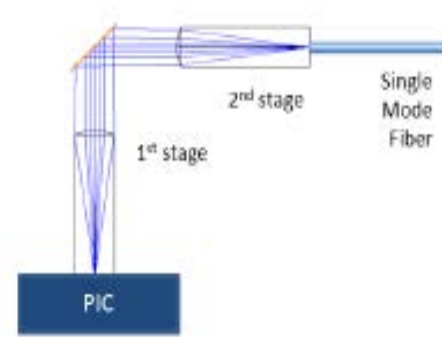


Fig. 22. Alternative techniques for fiber attach to PIC.

Microlens coupling

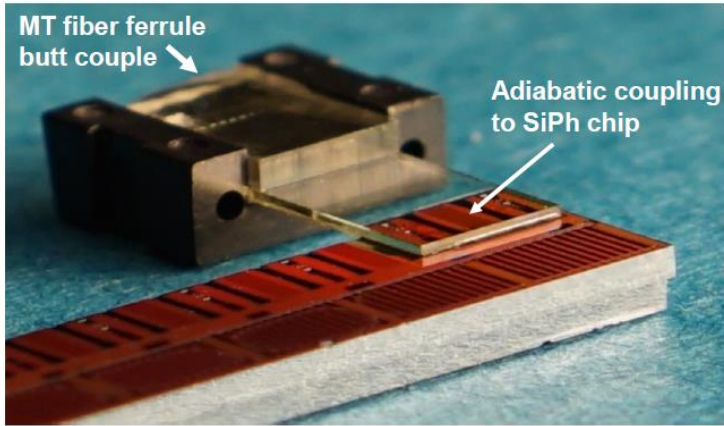
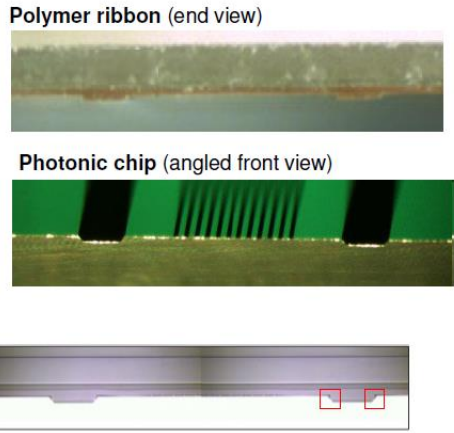
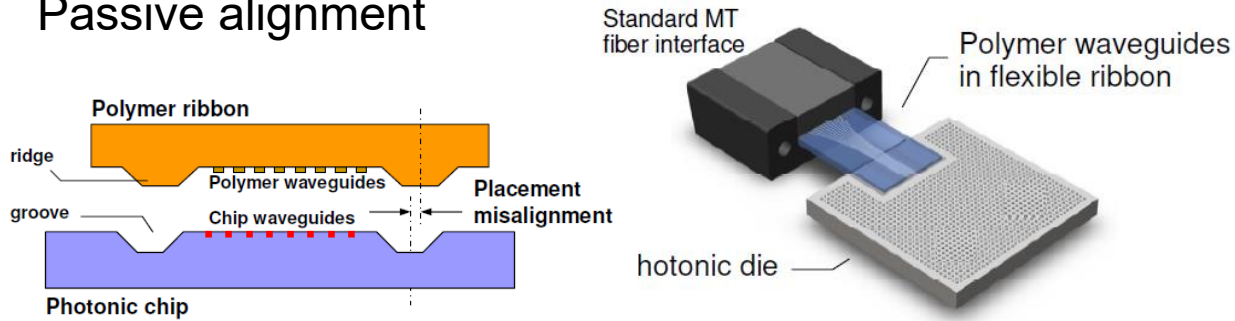
- Relaxed lateral tolerance
- Two stage optical train
- Enable pigtail free module



0,5 μm misalignment demonstrated

Evanescent coupling approach (IBM)

- Evanescent coupling between PIC and polymer waveguide
- Passive alignment



Evanescent coupling to SiN-on-Si waveguide layer (ST / Teem Photonics):

- **Broadband and single-mode** in O-band and C-band
- **Low loss** (< 1.5 dB from fiber to SiN)
- **Low PDL** (< 0.2 dB)
- **Alignment tolerant**

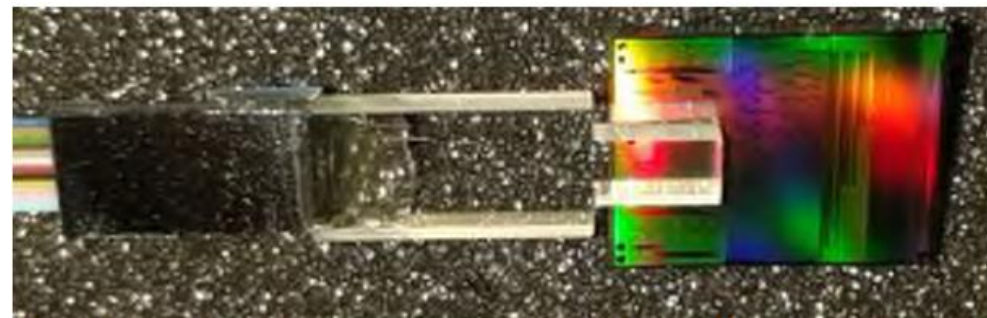
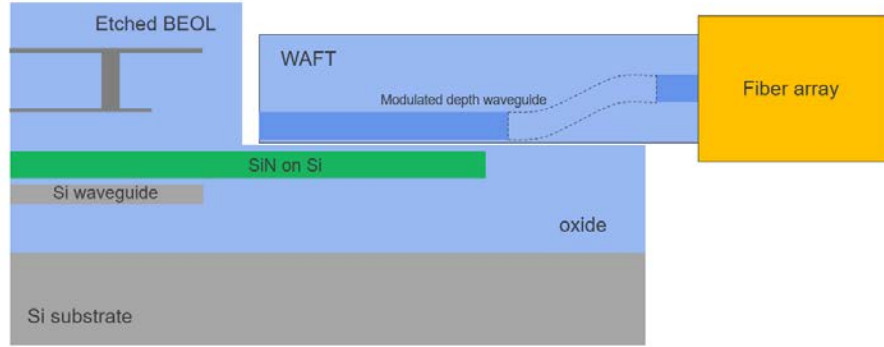
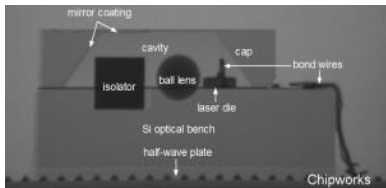


Fig 15 Glass interposer assembled Silicon Photonics Device with Cavity Etched BEOL



LASER INTEGRATION STRATEGIES



De Dobbelaere, OFC 2014

Micropackaging

Luxtera, Tyndall

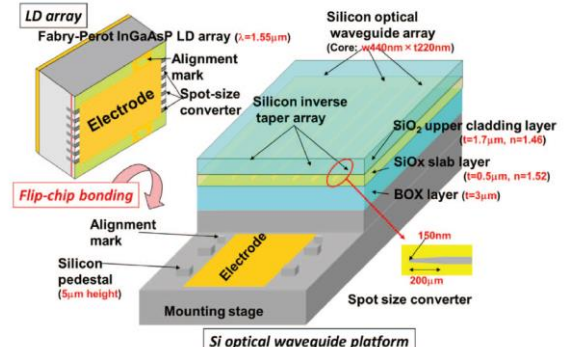
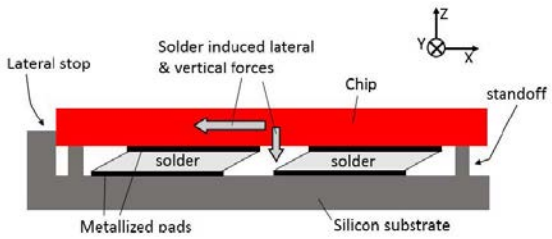


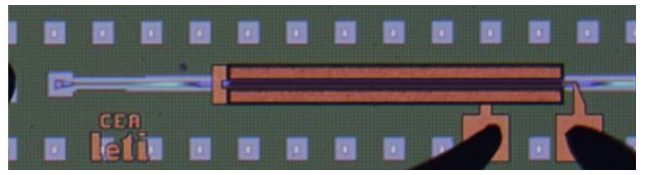
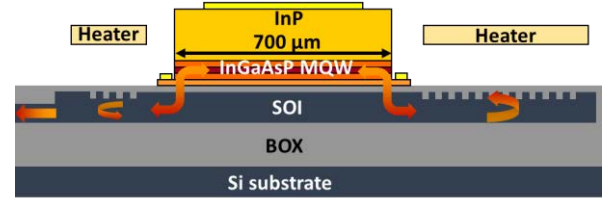
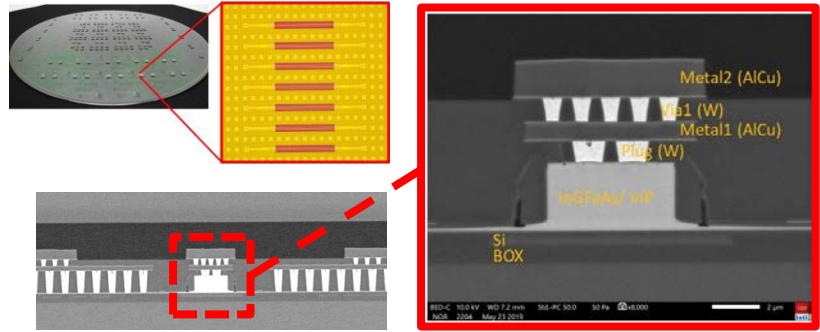
Fig. 1 Schematic of hybrid integrated light source with LD array on silicon platform made using SSC with SiO_x slab layer.

Shimizu et al., Trans. Jap. Inst. Of Elec. Pkg., 2014



Self aligned flip-chip (Hybrid)

Petra, IBM, IZM



B. Szlag, IEDM 2017

Direct bonding

Intel, UCSB, LETI

THERMAL CONSTRAINTS

- Photonic devices are temperature sensitive
- In co-packaging approach, proximity to the host chip could be a problem

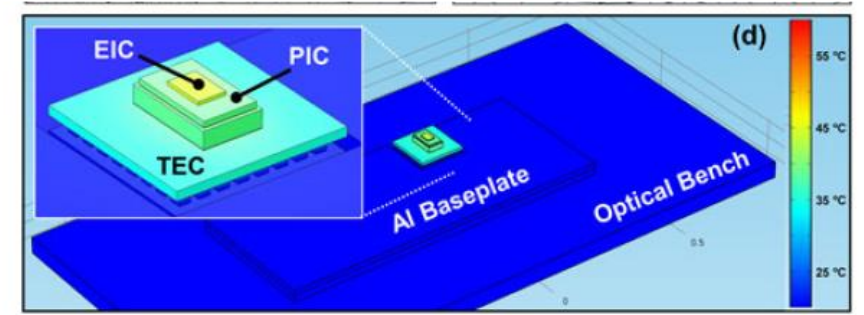
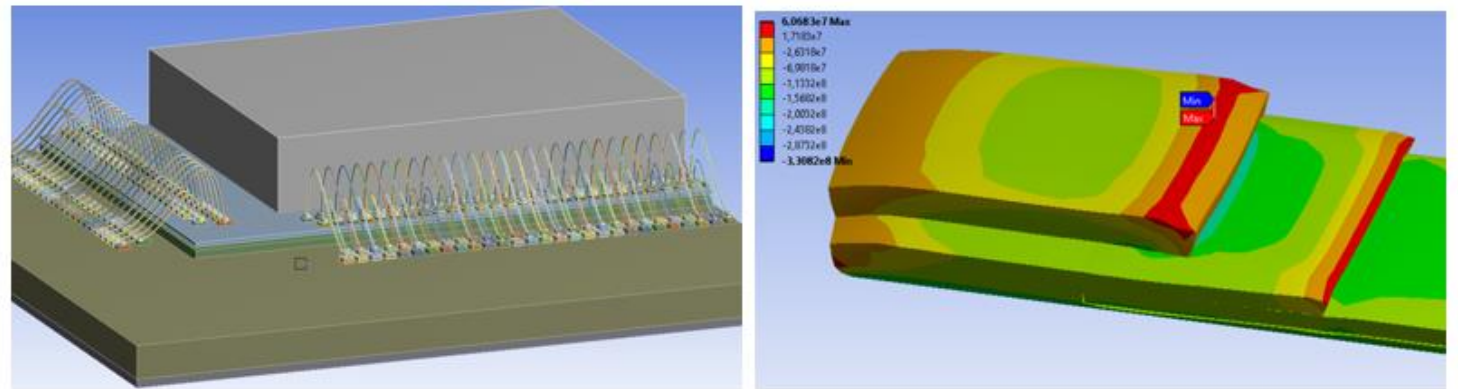
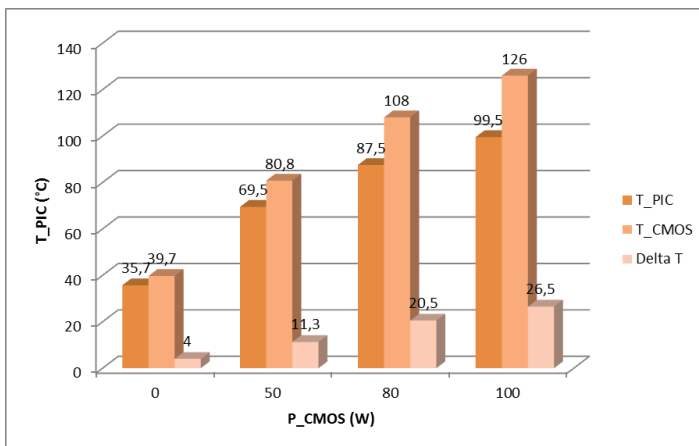
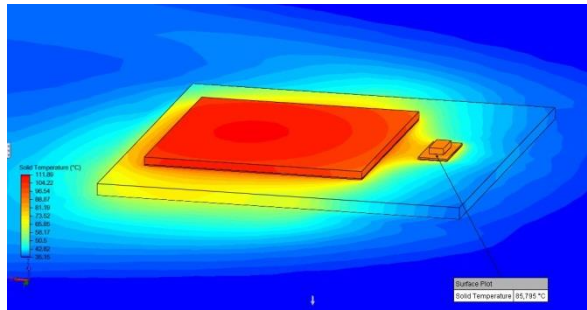


Fig. 8. (a)–(c) COMSOL model of the ONU, spanning the macroscopic dimensions of the TEC and Al baseplate to the microscopic dimensions of the CPB interconnects between the electronic-IC and PIC. (d) An example of the temperature map of the thermal stack and Al base-plate used to extract the temperature profiles in Fig. 9(a).

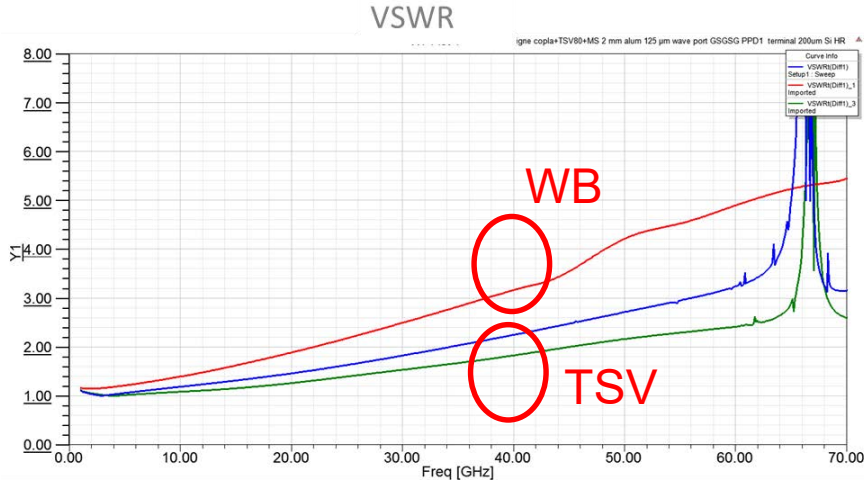
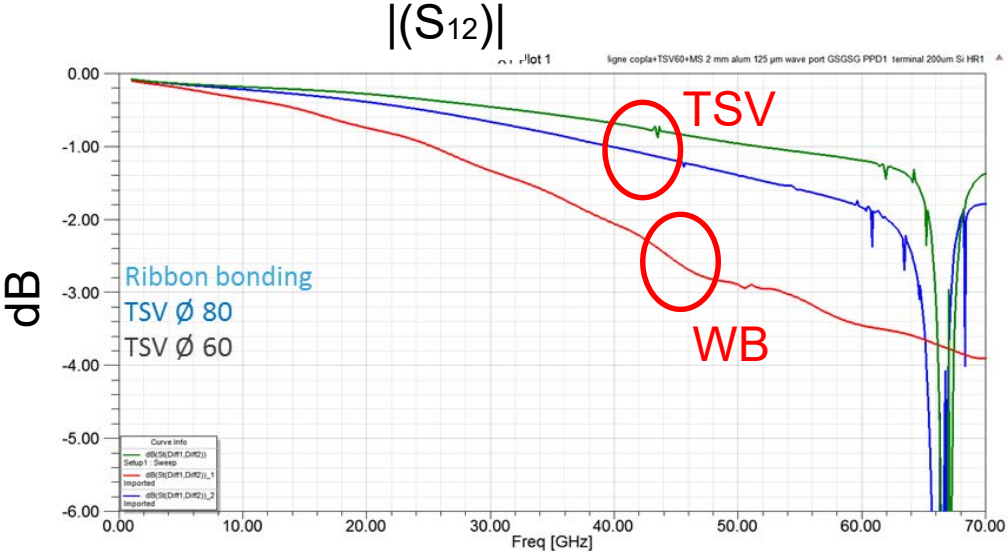
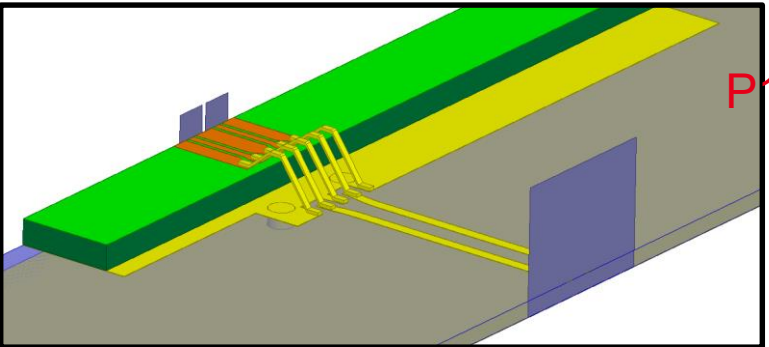
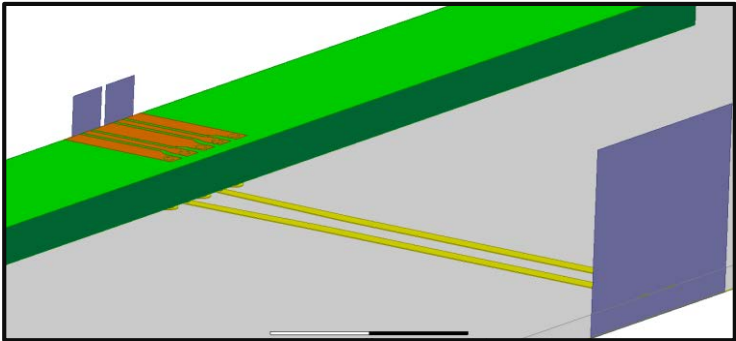
J. S. Lee et al., « Meeting the Electrical, Optical, and Thermal Design Challenges of Photonic-Packaging », *IEEE Journal of Selected Topics in Quantum Electronics*, vol. 22 n° 6, p. 409-417, nov. 2016



FEM thermo-mechanical simulation model of a wire-bond based PIC package module with the typical material deformation maps due to mechanical stress and/or heat within the package. Source: B. Sirbu / Fraunhofer IZM

RATIONALE FOR TSV

- RF S-parameters



25 Gbits/s 50 Gbits/s 75 Gbits/s

A STRATEGY FOR ELECTRONIC/PHOTONIC CONVERGENCE

THROUGH SOME EUROPEAN R&D INITIATIVES

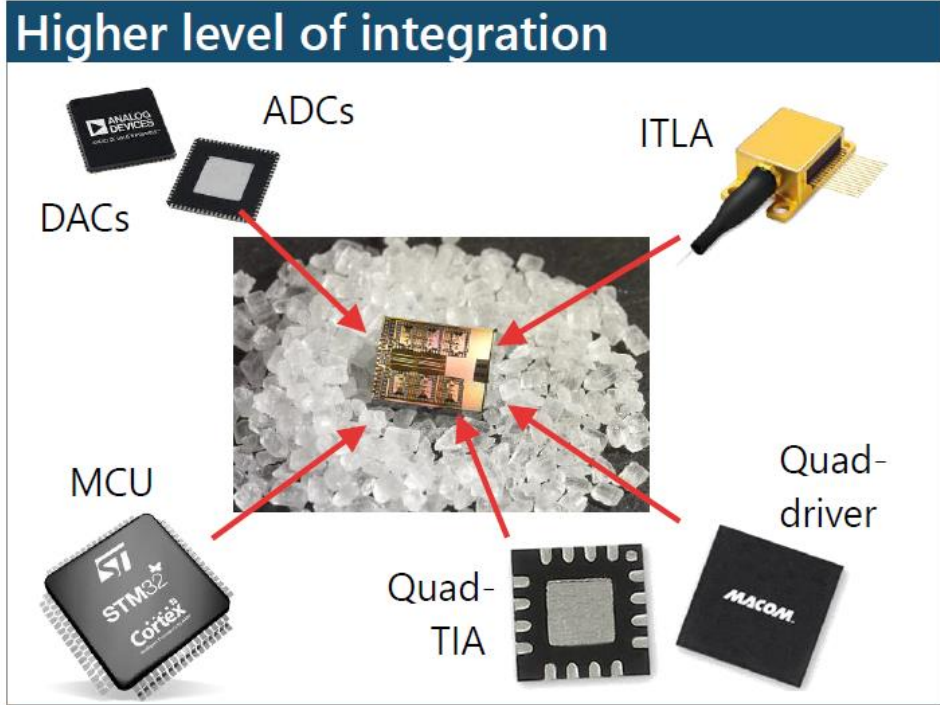


STEP1 : MASSIVE AUTOMATION



Cost

~80% of cost is in packaging



Automation & standards

- Single automated optical alignment step
- Leverage electronic IC infrastructure (e.g. flip-chip assembly)

Integration, automation & volume

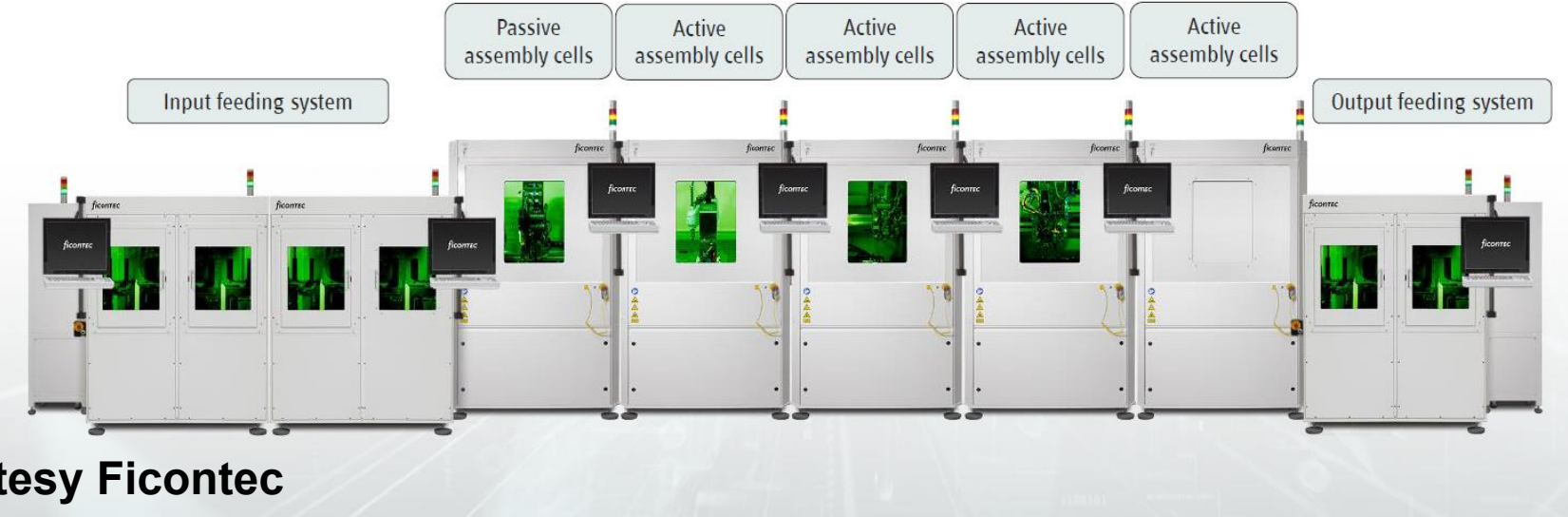
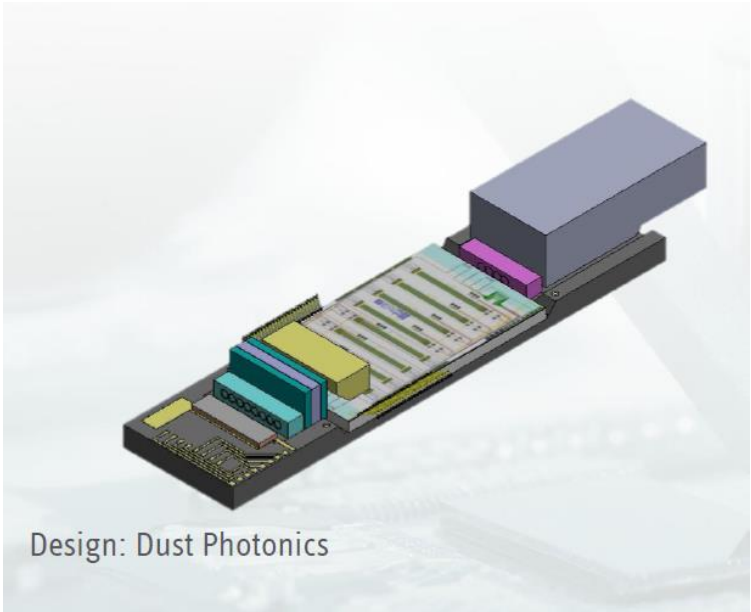
Courtesy of B. Wolfheil, ADVA

STEP1 : MASSIVE AUTOMATION



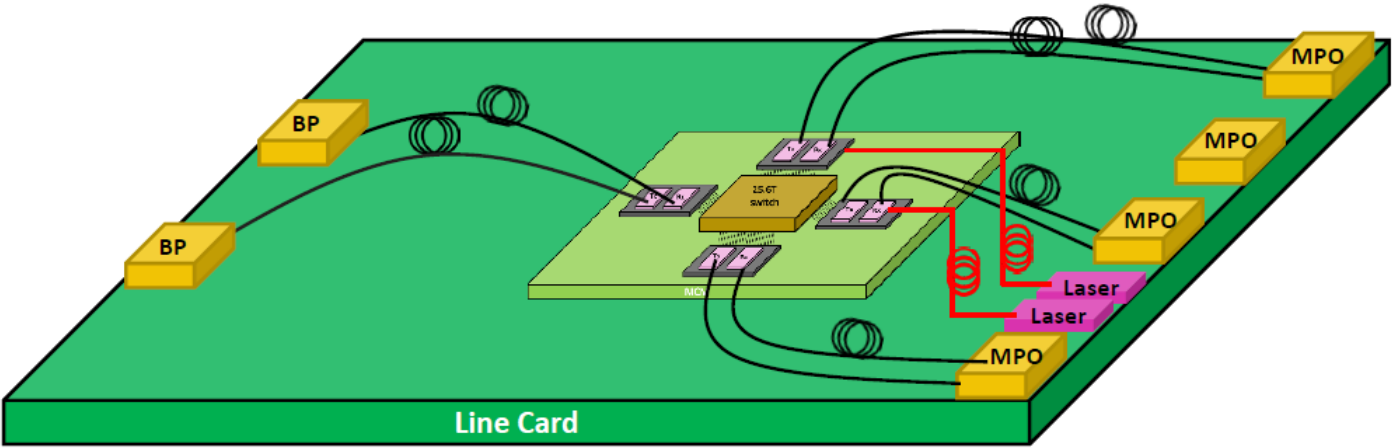
Active assembly machine

Passive assembly machine



Courtesy Ficontec

STEP2 : DENSE INTEGRATION / PASSIVE ASSEMBLY



- All fibers are routed to the passive front panel or backplane fiber connectors
- Module can be connected to the line card either using:
 - Socket – bad thermal connectivity, fibers may be glued in place during assembly
 - BGA – good thermal performance, fibers cannot go through reflow
- Air flow through the line card is improved due to the elimination of the pluggables on the front panel

The Chiplet approach

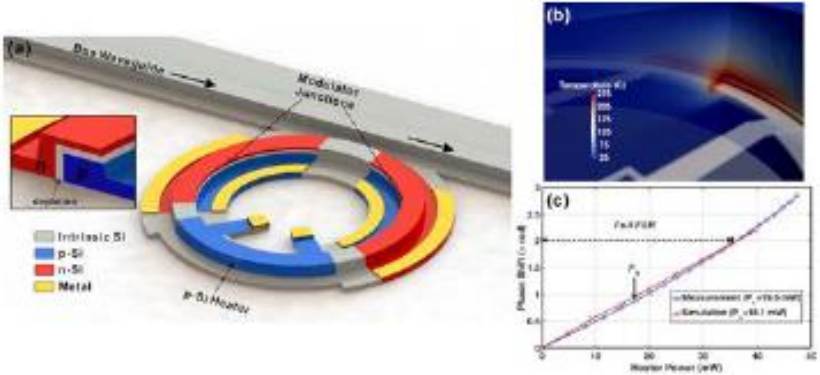
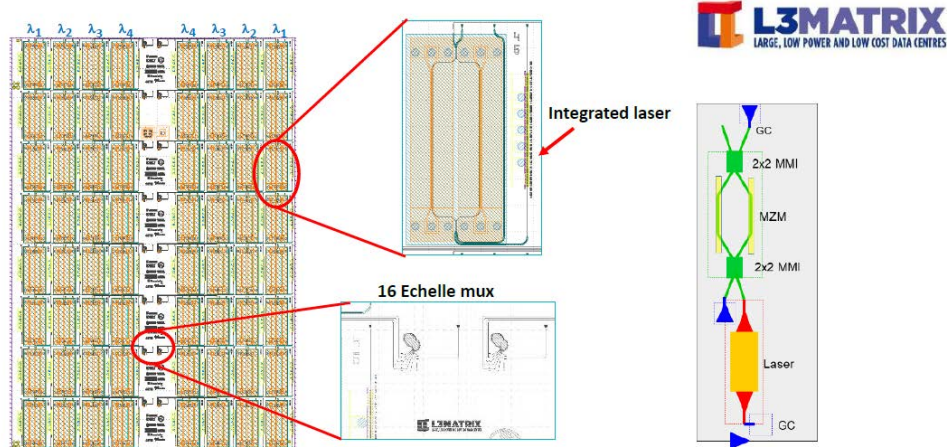


Figure 20: High speed microring with 45GHz BW, demonstrated by Intel [17].

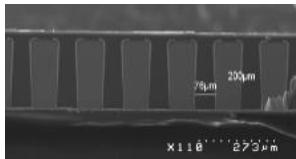
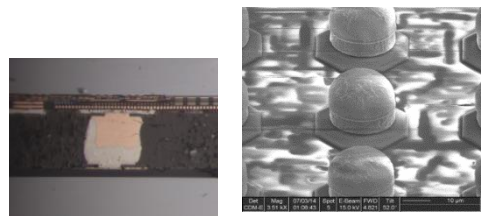
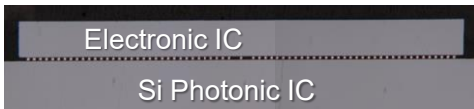
STEP2 : DENSE INTEGRATION / PASSIVE ASSEMBLY



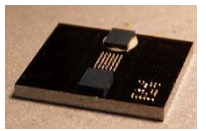
Wire bonding

Flip Chip

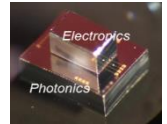
TSVs



Integration/Co-integration level



44 Bumps (SBB)



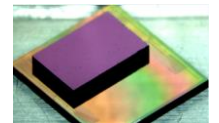
100 Bumps



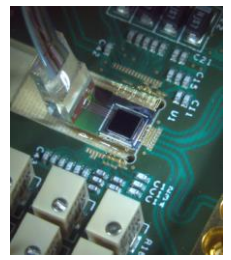
144 bumps



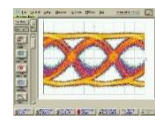
484 bumps



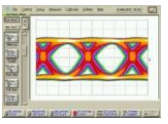
2091 bumps



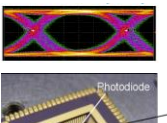
800 Gbps intra DC



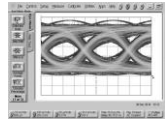
Module Rx 8Gbps Wire bonding



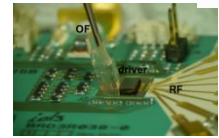
Module Rx 12,5Gbps Wire bonding



Module Rx 25Gbps Wire bonding



Module Rx 25Gbps Flip Chip



Module Rx 100 Gbps Chip On Board



200 Gbps Tx/Rx MBOM



200 Gbps/ (50G NRZ, WDM-2) 4 fibers (2 Rx/2Tx)

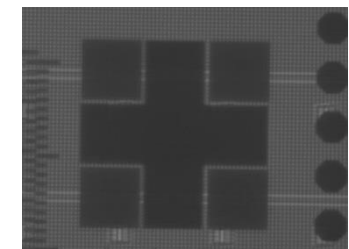
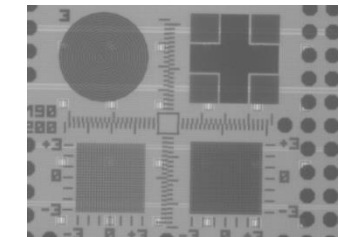
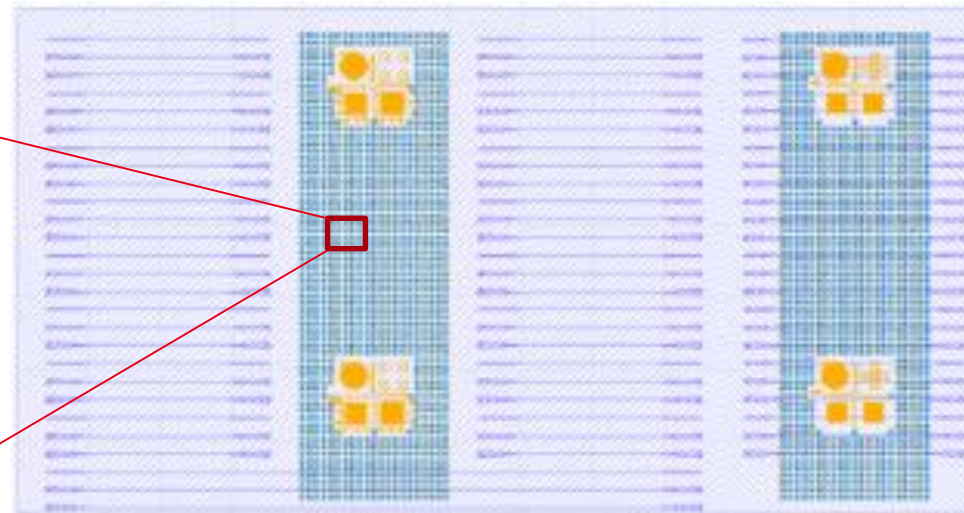
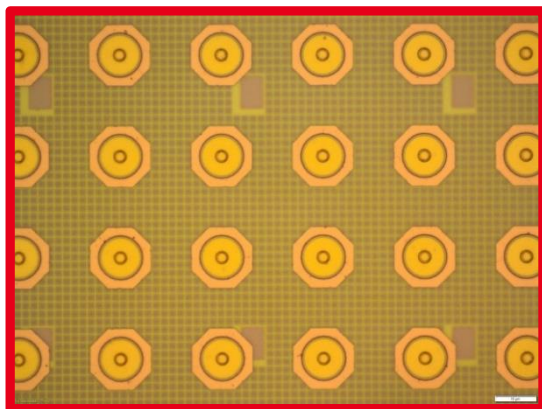
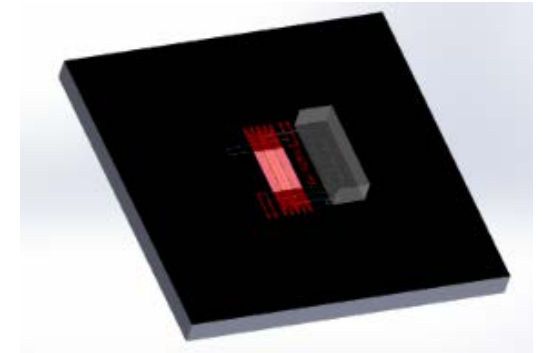
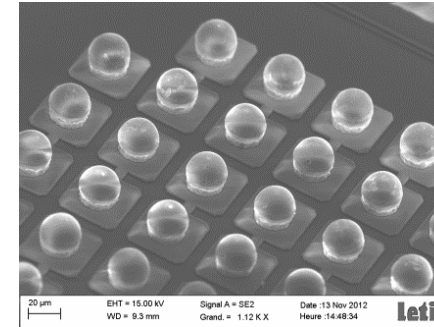
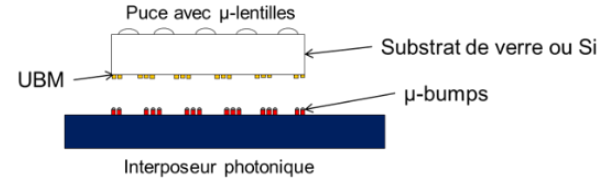
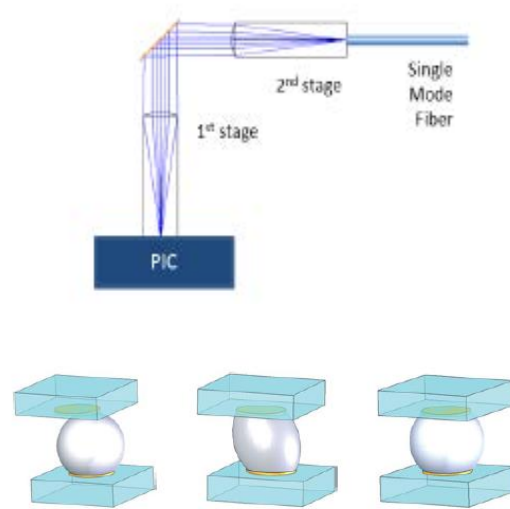
Enabler for 400Gbps++



2010 2011 2012 2013 2014 2015 2016 2017 2018 2019 2020 2021

SELF ALIGNMENT OF MICROLENSES

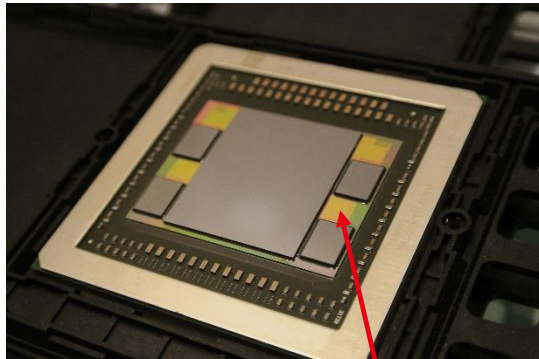
- Use of copper pillars to align first stage
- Through substrate IR observation of verniers
- $<0,5 \mu\text{m}$ misalignment obtained
- Robust process ($7\mu\text{m}$ offset is realigned)
- Compatible with High throughput bonding machine



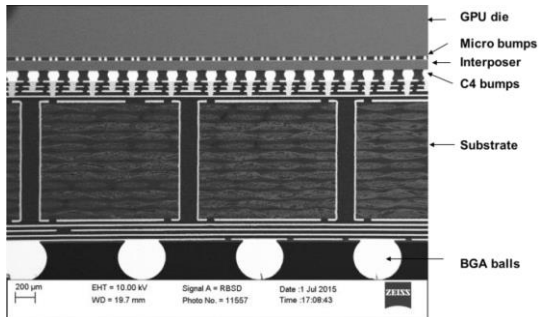
STEP 3 : THE ROAD TO PHOTONICS INTERPOSERS

Passive Interposer

Only electrical Routing



GPU AMD avec interposeur passif

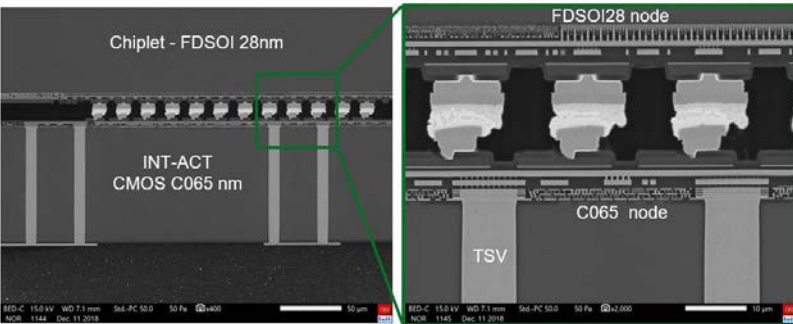


Interposeur passif AMD [1]

2016

Active Interposer

Electrical Routing
DC-DC conversion
Electrical Network On Chip

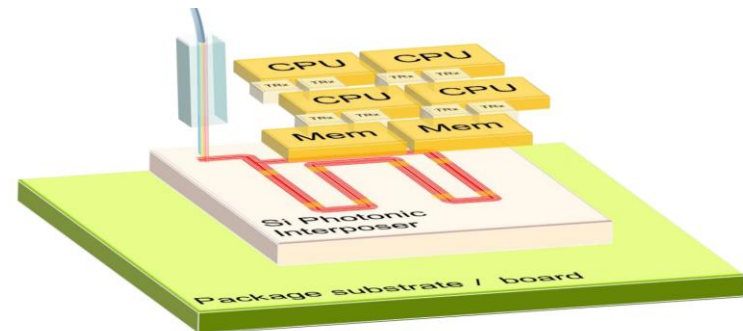
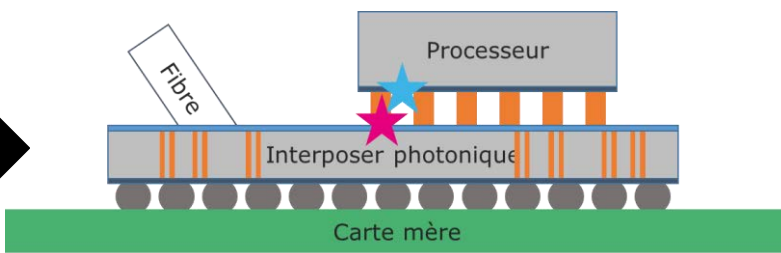


Interposeur actif INTACT [2]

2019

Photonic Interposer

Electrical Routing
Optical Network On Chip
OE conversion



202x?

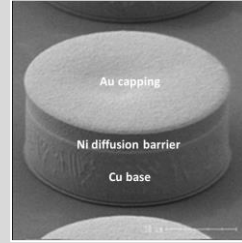
[1] C.-C. Lee et al., 2016 IEEE 66th Electronic Components and Technology Conference (ECTC)

[2] P. Coudrain et al., 2019 IEEE 69th Electronic Components and Technology Conference (ECTC)

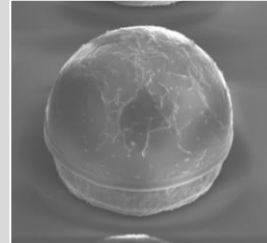
Courtesy of P. Tissier

3D TECHNOLOGIES - LAB STATE OF THE ART

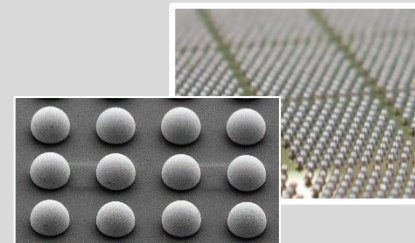
Connecting



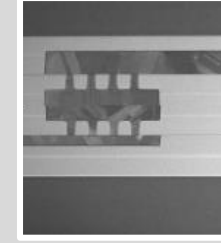
Copper pillars ($\varnothing 10\mu\text{m}$)



Copper- bumps ($\varnothing 10\mu\text{m}$)

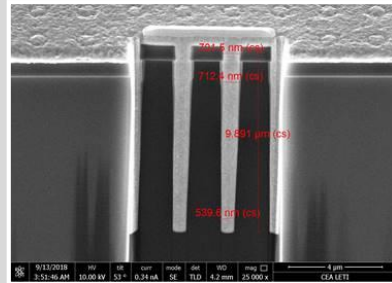


Bumping ($\varnothing 70\mu\text{m}$)– Balling ($\varnothing 300\mu\text{m}$)

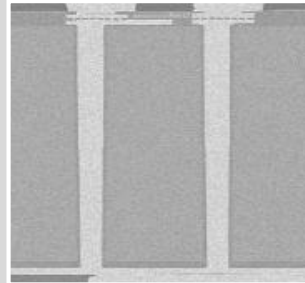


Hybrid bonding (LIFT)

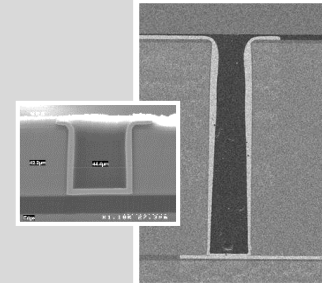
TSV



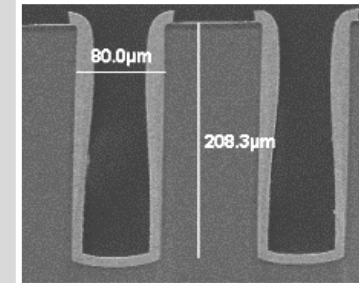
TSV High Density AR10 $\varnothing 1\mu\text{m}$



TSV mid AR10

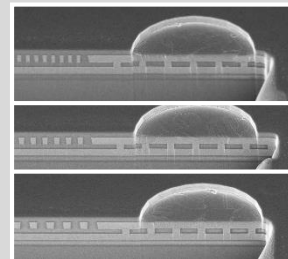


TSV last AR 0,5 → 5

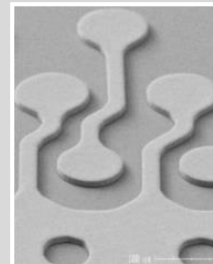


TSV last power (thick Cu-liner)

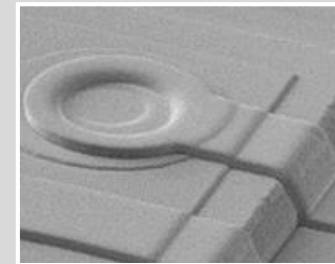
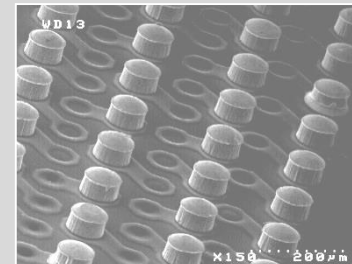
Rerouting



Front-side damascene (Pitch 400nm)



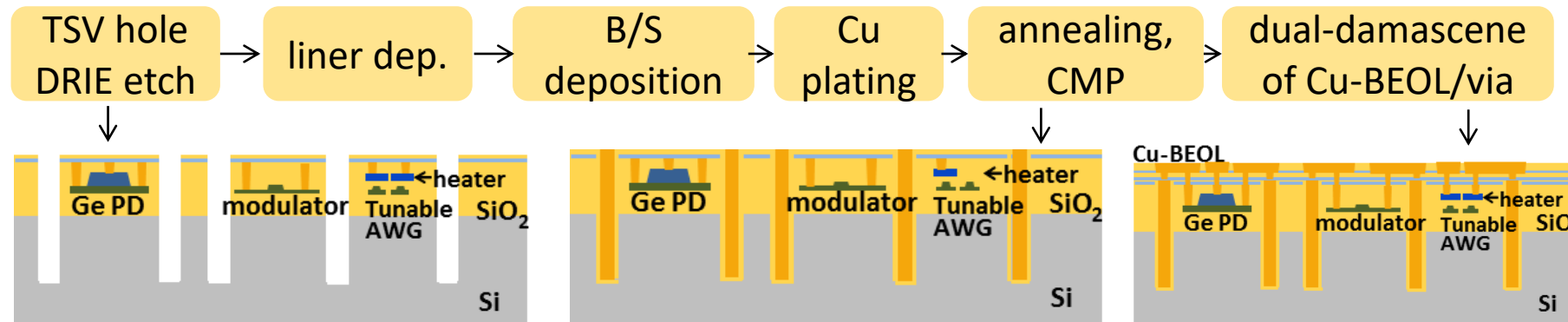
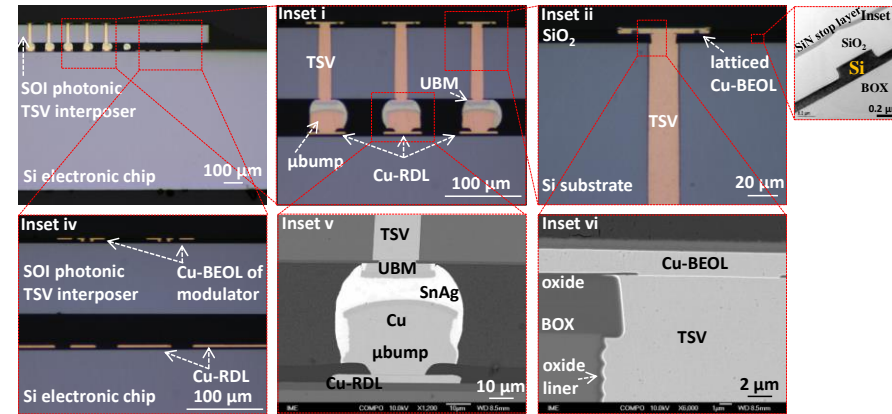
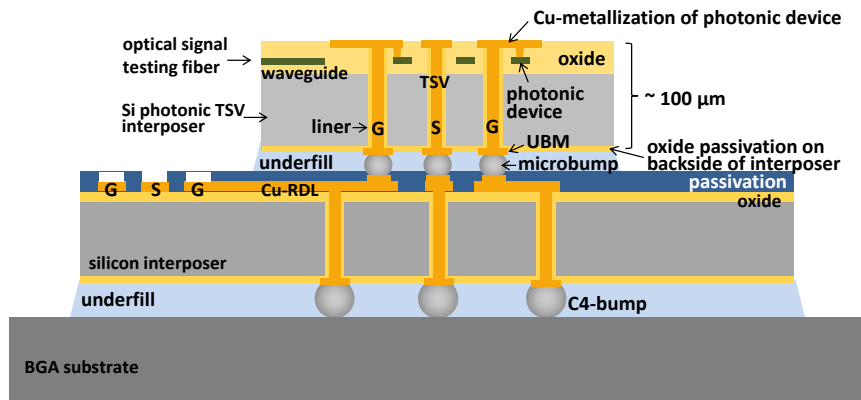
Back-side RDL co-integration (Pitch 20 μm)



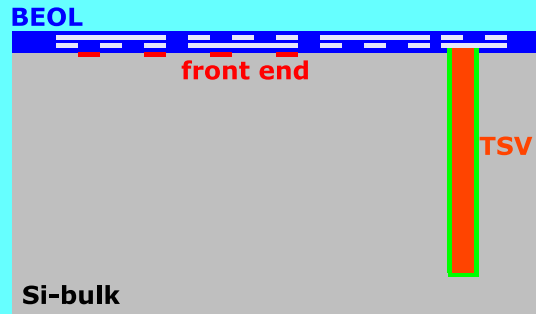
Cu conformal routing

Courtesy of J. Charbonnier

FIRST PHOTONIC INTERPOSER (IME/ASTAR, 2016)

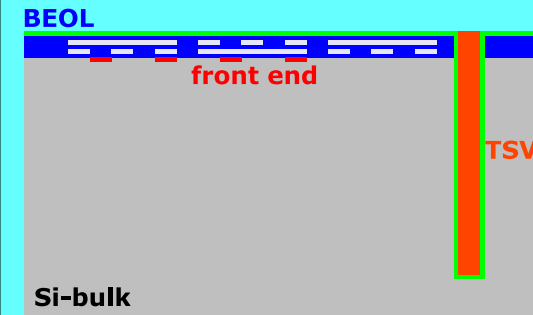


Via first or middle;



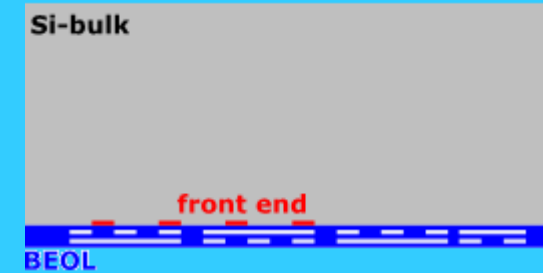
- TSV integration before FEOL or after FEOL / before BEOL
- Processes established at IDMs

Via last;

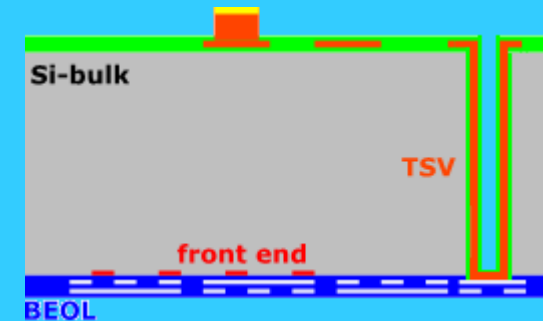
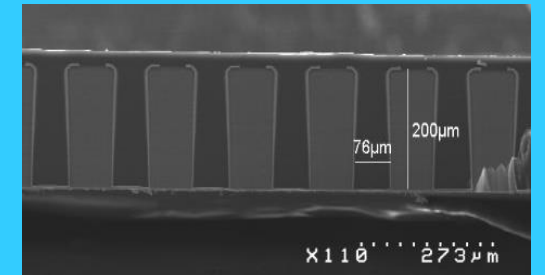


- TSV integration after complete wafer processing
- TSV through thick BEOL oxide
- Requires keep out zones in FEOL and BEOL for TSV integration

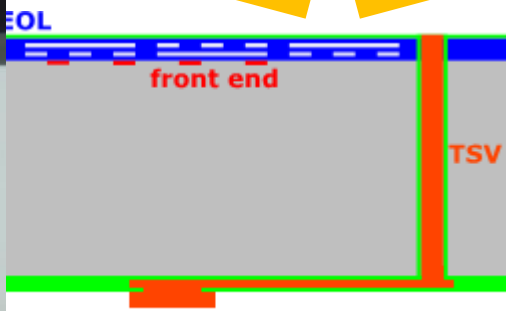
Back Side Via last



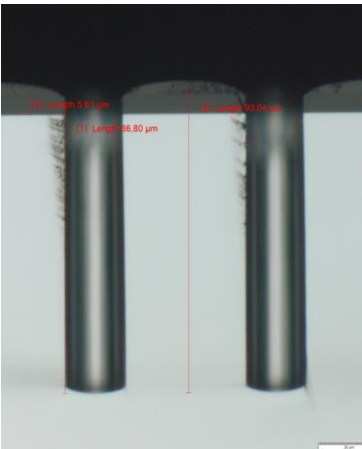
- TSV integration after complete wafer processing
- Requires landing pads in BEOL for prepared TSV connection



- Support wafer bonding
- Wafer backside thinning
- TSV formation with access to landing pads
- Metall liner and back side RDL formation
- Support wafer de-bonding (if required)



- Support wafer bonding
- Wafer backside thinning
- TSV reveal
- Backside RDL and bump formation
- Support wafer de-bonding



Courtesy of B. Sirbu, Fraunhofer IZM.

Dia. 10~12 μm , height 100 μm
 TSV mid process

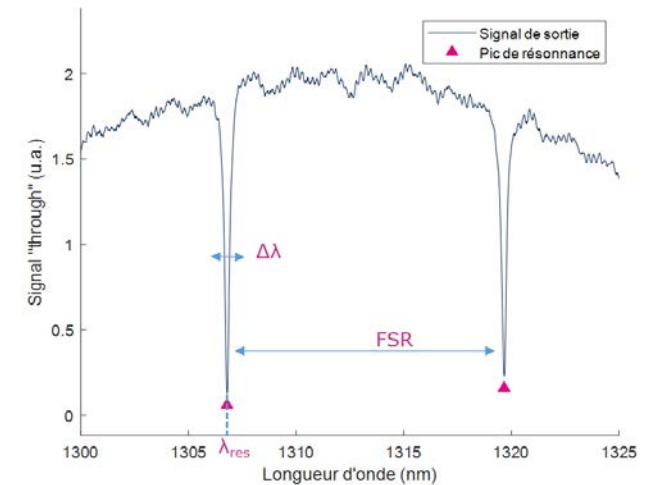
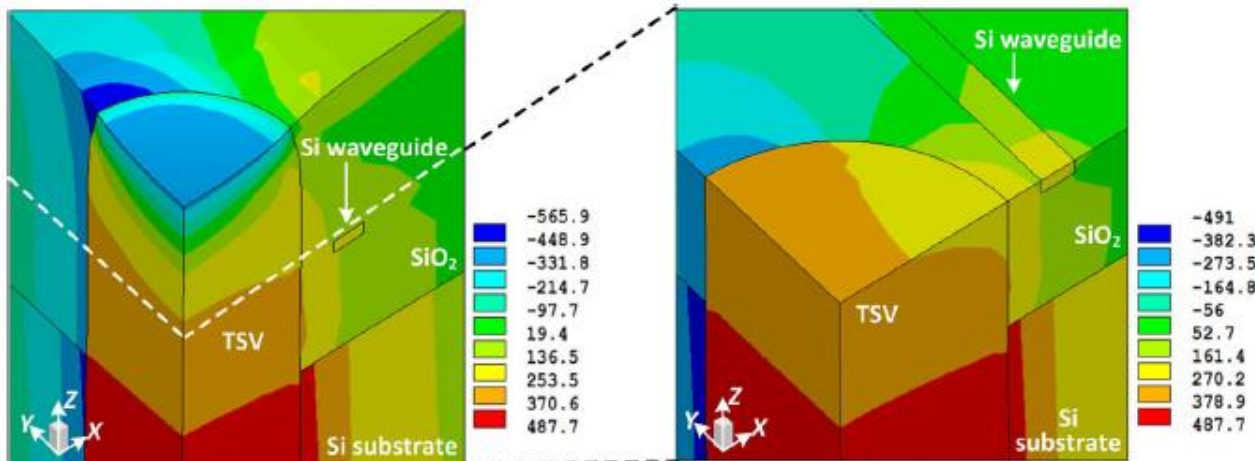
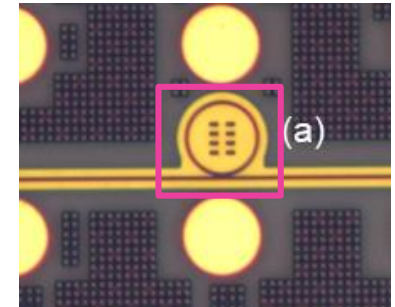
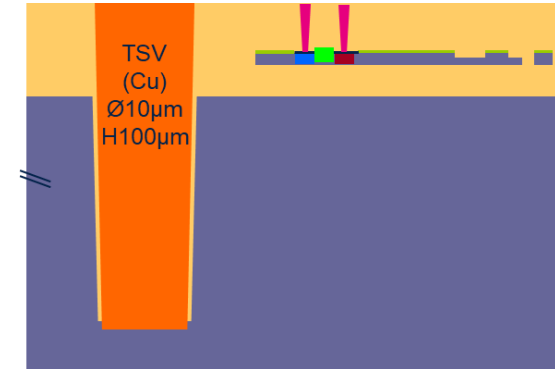
Does TSV interfere with photonics structures?

CTE differential

Thick BOX (can lead to warpage then stress)

Optomechanical effect

Keep Out Zone for Designers ?



- Fabrication of Ring filters with TSV –last, on ST + LETi 300mm platform
 - Measurement of X-Ray diffraction (Synchrotron)
- No evidence of high stress due to the TSV above 5µm distance

Confirmed by mixing simulated field of stress with FDTD optical simulations (Lumerical)

$$\Delta n_{eff} = 5,8 \cdot 10^{-4}$$

Experimental O/E measurements of Ring Filters

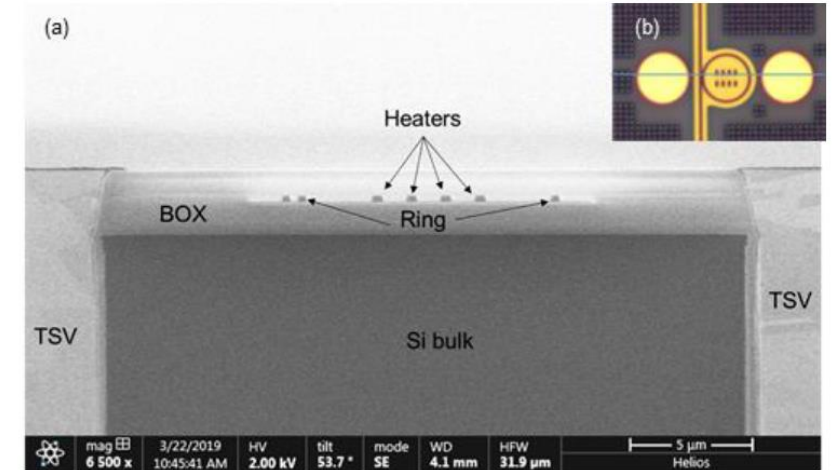
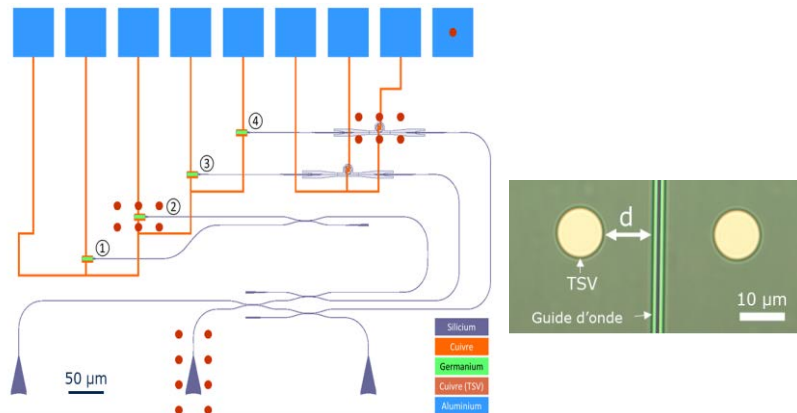
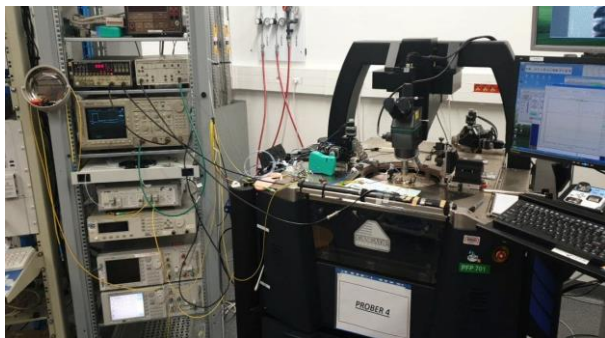
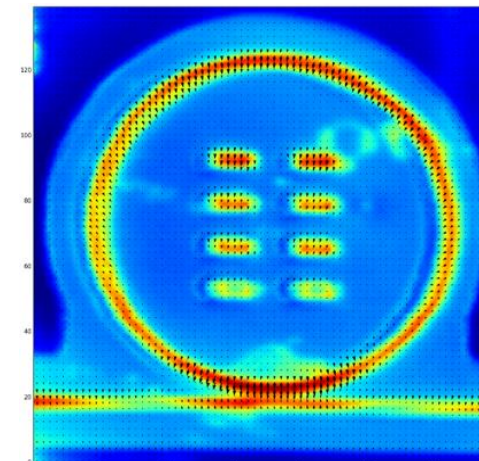
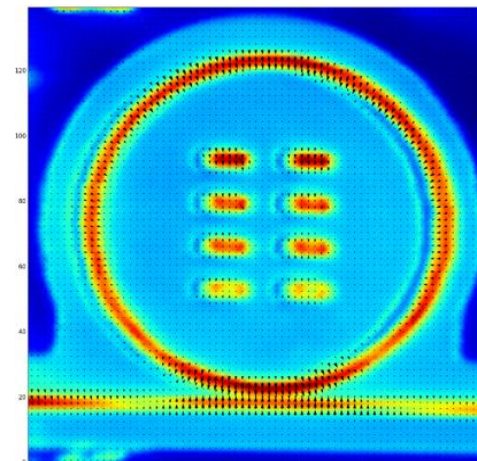


Fig. 4. a) SEM cross section of the TSV-surrounded ring before BEOL, b) optical top view of the ring and its TSVs and corresponding cross section plane

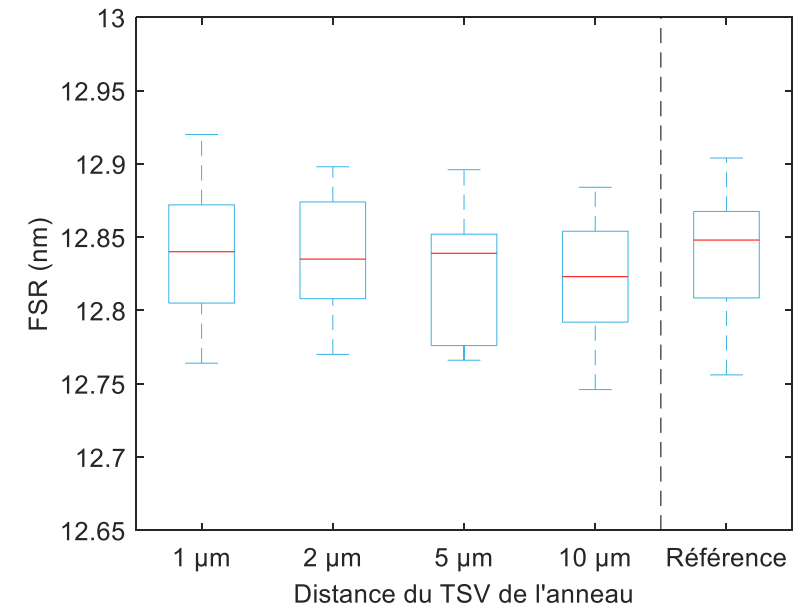
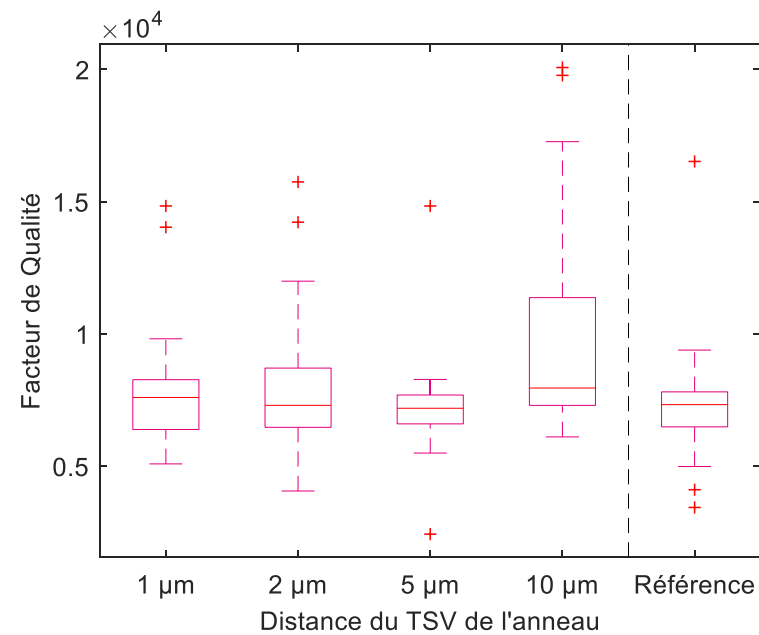
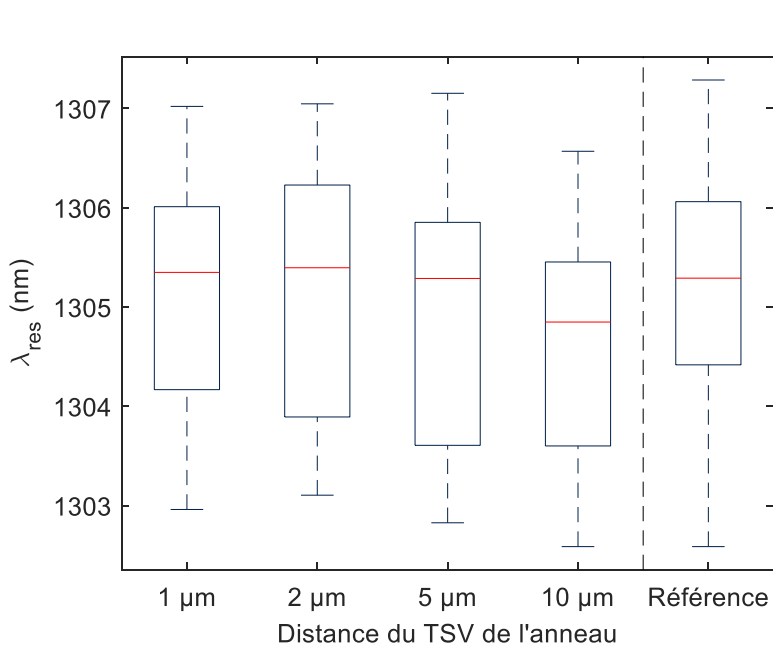
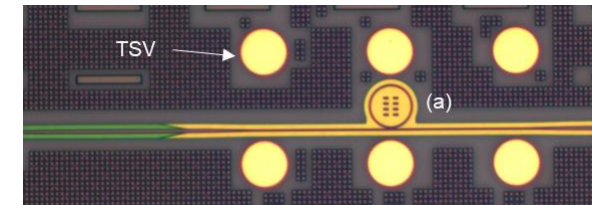


Anneau de référence



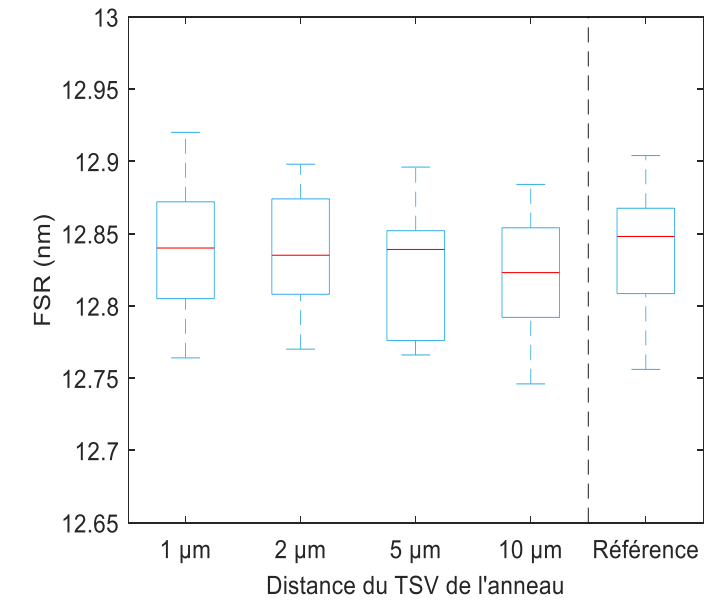
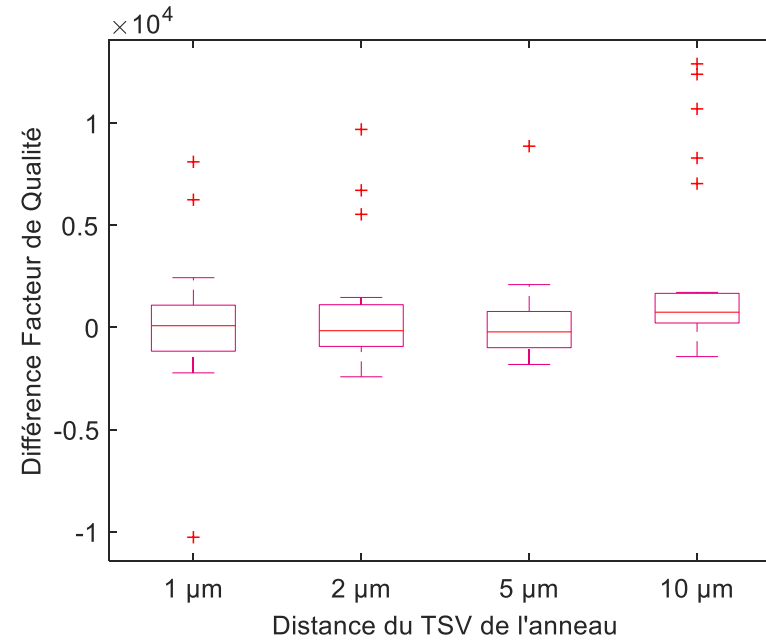
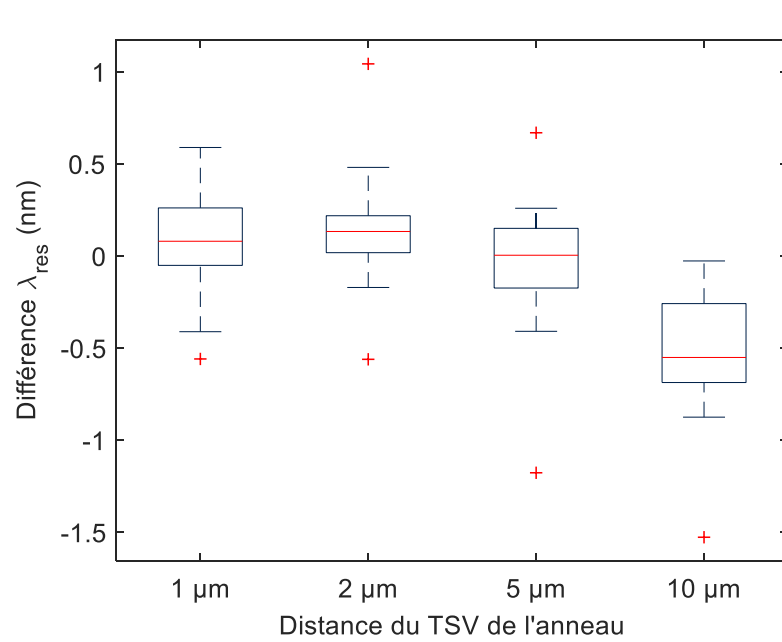
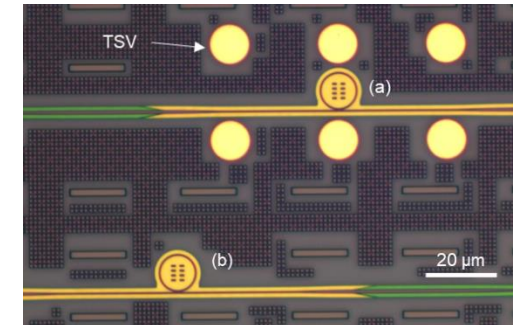
Anneau avec TSV à 5 µm

- Ring features as a function of TSV-Ring distance



TSV effect is below process dispersion

Comparison with reference ring



No measured impact of TSV, KOZ > 1 μm is safe

Silicon Photonics has widespread at every stage of the Internet Network, now targeting emerging applications

This lead to a new paradigm in terms of packaging & assembly

- Mass manufacturing is needed
- Advanced packaging technologies will be applied
- The main driver will always be the **Cost !**

SiPho packagers have to face some challenges:

- Laser integration
- Thermal constrains
- Fiber connector
- 3D integration

CEA LETI with ST microelectronics achieve a Photonics Interposer using Via Mid TSV

=> Keep Out Zone >1 μ m is OK for designers

Acknowledgements :

Karim Hassan

Jean Charbonnier

Pierre Tissier

Quentin Wilmart

Sergio Nicoletti

Daivid Fowler

Bogdan Sirbu (IZM)

Tolga Tekin (IZM)

Paraskevas Bakopoulos (nVIDIA)

Leti Photonics team

Leti Packaging team

MASSTART project partners



Q & A

Procédés de fabrication de l'interposeur photonique

